



# TEVELT (2)

## RESEARCH AND DEVELOPMENT TECHNICAL REPORT CORADCOM-76-0040-F

MANUFACTURING METHODS AND TECHNOLOGY PROGRAM OF INJECTION LASER DIODES FOR USE IN FIBER OPTIC COMMUNICATIONS.

ALBERT GENNARO

LASER DIODE LABORATORIES

1130 SOMERSET STREET

NEW BRUNSWICK, N. J. 08901



31 MARCH 1981

FINAL REPORT FOR PERIOD JULY 1976-FEBRUARY 1981

APPROVED FOR PUBLIC RELEASE; DISTRIBUTION UNLIMITED

THIS DOCUMENT IS BEST QUALITY PRACTICADIA.
WHE COPY TURNISHED TO EDG CONTAINED A
SIGNIFICANT NUMBER OF PAGES WHICH DO NOT
REPRODUCE LEGIBLY.

## **CORADCOM**

U S ARMY COMMUNICATIONS RESEARCH & DEVELOPMENT COMMAND FORT MONMOUTH, NEW JERSEY 07703

81 7 16 113

#### DISCLAIMER STATEMENT

The findings in this report are not to be construed as an official Department of the Army position unless so designated by other authorized documents.

#### DISPOSITION INSTRUCTIONS

Destroy this report when it is no longer needed. Do not return it to the originator.

#### ACKNOWLEDGEMENT STATEMENT

This project has been accomplished as part of the U.S. Army Manufacturing Methods and Technology Program which has as its objective the timely establishment of manufacturing processes, techniques, or equipment to insure the efficient production of current or future defense programs.

## **DISCLAIMER NOTICE**

THIS DOCUMENT IS BEST QUALITY PRACTICABLE. THE COPY FURNISHED TO DTIC CONTAINED A SIGNIFICANT NUMBER OF PAGES WHICH DO NOT REPRODUCE LEGIBLY.

UNCLASSIFIED SECURITY CLASSIFICATION OF THIS PAGE (When Date Entered) READ INSTRUCTIONS
BEFORE COMPLETING FORM \* REPORT DOCUMENTATION PAGE 2. GOVT ACCESSION NO. 3. PECIPIENT'S CATALOG NUMBER ALFORT MUNICA CORADCOMH76-0040-F AD-A101 481 TITLE (mod Schutte) S. TYPE OF REPORT & PERIOD COVERED Final Report INJECTION LASER DIODES FOR FIBER OPTIC 7/30/76-2/28/81 COMMUNICATIONS 6. PERFORMING ORG. REPORT NUMBER B. CONTRACT OR GRANT NUMBER(#) 7. Att 1 40 R(a) Albert Gennaro DAAB07-76-C-0040 ) 9. PERFORMING ORGANIZATION NAME AND ADDRESS 10. PROGRAM ELEMENT, PROJECT, TASK AREA & WORK UNIT NUMBERS Laser Diode Laboratories 2769778 1130 Somerset Street New Brunswick, N. J. 08901 12 REPORT DATE II. CONTROLLING OFFICE NAME AND ADDRESS USACORADCOM March 81 FT. Monmouth, N. J. 07703 J. NUMBER OF PAGES 152 Attn: DRDCO-PC-D (HUN) IN MONITORING AGENCY HAME & ADDRESSILL dillerent from Controlling Office) Unclassified 15a. DECLASSIFICATION DOWNGRADING SCHEDULE 16. DISTRIBUTION STATEMENT (of this Report) Approved for public release; distribution unlimited. 17. DISTRIBUTION STATEMENT (at the abstenct entered in Black 20, if different from Report) IB SUPPLEMENTARY NOTES 19. KEY WORDS (Continue on teverse side if necessary and identity by block number) Injection Laser Diodes Fiber Optic Communications Gallium Aluminum Arsenide Double Heterojunction Laser Diode

(9) At THACT (1 crimin on reverse side if necessers and identify by block number)

The design and fabrication of injection laser diodes for use in fiber optic communications is discussed with regard to material synthesis, chip configuration, and device assembly in manufacturing environment. The opto-electronic source is based on the GaMr-GaMlAs double heterojunction structure and consists of a parallel array of lasers formed by the application of triple stripe geometry to the surface of the epitaxial wafer. The

DD LAN 73 1473 EDITION OF THOU 65 IS OBSOLETE

SECURITY CLASSIFICATION OF THIS PAST (When Data Entered)

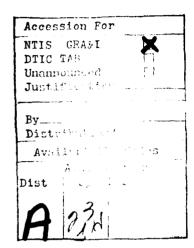
4/21-6

ti

SECURITY CLASSIFIC ATION OF THIS PAGE(Ation Data Enters ()

monolithic triand of discrete lasing elements is mounted in a high frequency package which incorporates a high quality optical window.

1



UNCLASSIFIED
STITUTE CLASSIFICATION OF THIS PAGE (When Date Fintered)

#### TABLE OF CONTENTS

Sectio	<u>r:</u>		Page
I		Introduction	1
II		Device Design Requirements and Performance Specifications	2-9
	2.1	Electro-Cptical Characteristics	2
	2.2	Device Structure	2-7
	2.3	Array Configuration	7
	2.4	Package Requirements	7-9
III		Manufacturing Methods and Technology Engineering	9-54
	3.1	Material Technology	9
	3.1.1	Synthesis of Device Structure via LPE	9
	3.1.1.1	Liquid Phase Epitaxial System	9-17
	3.1.1.2	Growth Process for the Synthesis of Double Heterojunction Structures	17-24
	3.1.2	Wafer Processing for Monolithic Triple Stripe Geometry Module Fabrication	24~29
	3.2	Packaging Technology	29
	3.2.1	Package Design	29-40
	3.2.2	Assembly Technique	41-49
	3.3	Device Evaluation and Testing	50
	3.3.1	Test Equipment	50-70
IV		Summary of Pilot Line Test Results	71-80
v		Pilot Line Rate Report	81-82
VI		Volume Production Plan	83-86
Appe	ndix A	Product Capability Demonstration	87-94
Appendix B		SCS-516 Specifications	
Appendix C		Distribution List	

#### LIST OF FIGURES

Figure		Page
1	Schematic Representation of the Epitaxial Structure for Fabrication of Stripe Geometry Double Heterojunction Injection Laser Diodes	. 5
2	Monolithic Triple Stripe Geometry Laser Diode Module Configuration	. 8
3	Outline of Laser Diode Pill Package	.10
4	Detail of Injection Laser Module Mount	.11
5	Block Diagram of Liquid Phase Epitaxial Systems Currently in Use at Laser Diode Laboratories	.13
6	Photograph of Liquid Phase Epitaxial Reactors at Laser Diode Laboratories	. 15
7	Schematic Diagram of Gas Control Subsystem	. 16
8	Photograph of Eight Bin Ultra High Purity Graphite Epitaxial Boat	. 18
9	Sequence of Operations for Liquid Phase Epitaxial Synthesis	. 1.9
10	Temperature Program Used in the Liquid Phase Epitaxial Growth of Double Hetero-junction Structures for Monolithic Stripe Geometry Laser Diodes	. 22
11	Photograph of Typical Double Heterojunction Structure Required for the Manufacture of Monolithic Stripe Geometry Injection Laser Diodes	. 23
12	Surface Morphology of the As-Grown Hetero-	· 25
13	Process Flow Diagram for the Fabrication of Monolithic Stripe Geometry Injection Laser Arrays	. 26
14	Scribing Apparatus for Cleaving Epitaxial	20

#### LIST OF FIGURES (Cont'd)

Figure	Page
15	Photograph of Triple Stripe Geometry Applied to Surface of an Epitaxial Wafer30
16	Photograph of Individual Triple Element Modules
17	Pill Package-Mounting Base (Positive Electrode)
18	Pill Package-Spacer (Ceramic Insulator) 33
19	Pill Package - Cover Plate (Negative Electrode) 34
20	Pill Package - Optical Window
21	Pill Package - Epoxy Preform
22	Photograph of Optical Window and Epoxy Preform 38
23	Pill Package Blanks 40
24	Blow Up of Pill Package Injection Laser Diode Assembly
25	Bonding Fixture with Packages Clamped for Bonding
26	Pill Package Assembled and Milled 44
27	Rubber Lapping Pad 45
28	Photograph of Lapping Apparatus Used to Obtain Flat Window Mating Face 46
29	Pill Package-Laser Assembly Flow Chart 48
30	Completed Package Configuration 49
31	Transistor 10 ns Pulser 51
32	Transistor Test Pulser Assembly 52
33	Revised 10 MHZ ILD Driver (Single Position) Circuit Schematic
34	Clock and Control Circuit for Transistor Pulser

#### LIST OF FIGURES (Cont'd)

Figure	Page
35	Local Clock Buffer for Burn-In Rack 56
36	Burn-In Position Board with Edge Connector Fingers
37	Avalanche Diode Regulator-Detector
38	APD Power Detector System 60
39	Internal Structure Power Detector Head 61
40	Measurement of Beam Width 63
41	Photo of EG&G with Pulser on Gonimeter on Rail
42	Double Exposure Illustrating Gonimeter Operation
43	Measurement of Wavelength and Spectral Width
44	Stripe Width Measurement System 68
45	Triple Stripe Video Display 69
46	Measurement of Ip and Peak Power 70
47	Testing Cycle
48	Flow Chart - First Article
49	Flow Chart - Production Testing 74
50	Acceleration Fixture
51	10,000 HR Life Test 80

#### LIST OF TABLES

Table		Page
1	Electro-optical Performance Characteristics of the Injection Laser Diode for Fiber Optic Communications	. 3
2	Melt Compositions for Double Heterojunction Epitaxial Synthesis	. 20
3	Process Conditioning - All Units	, <b>7</b> 5
4	Group A Testing	. 77
5	Group B Testing	. 78
6	Group C Testing	. 79
7	Pilot Line Rates	. 82
8	Volume Production Schedule	. 84
9	Volume Production Rates	. 85
10	Additional Volume Production Requirements	. 86

#### SECTION I

#### INTRODUCTION

The primary objective of this Manufacturing Method and Technology Engineering Program is threefold. First, the Injection Laser Diode for use in Fiber Optic Communications as outlined in Specification SCS-516 must be transferred from a developmental device to a manufactured commercial product without adversely affecting the performance characteristics of the device. Secondly, the manufacturing methods and techniques necessary for the production of the laser diode be developed and implemented to insere the highest degree of device quality and reliability at a reasonable cost. Thirdly, verification of device performance and quality for injection lasers produced in a manufacturing environment must be carried out by means of rigorous testing and evaluation to demonstrate the technical adequacy of the manufacturing methods developed under this contract.

This report describes the techniques and methods used to attain the goals as described above. In particular laser chip concepts and design, package concepts and design and environmental and electrical testing were key areas and established the emphasis required to achieve the successful completion of the program.

#### SECTION II

#### DEVICE DESIGN REQUIREMENTS AND PERFORMANCE SPECIFICATIONS

#### 2.1 Electro-Optical Characteristics.

The performance characteristics of the Injection Laser for use in Fiber Optic Communications are described in detail in Technical Specification SCS-516. The device may be generally described as a double-heterojunction (DH) GaAs - GaAlAs semiconductor laser capable of high data rate transmission at an emitting wavelength of 820 nm at room temperature. In addition, the device must be fiber optic compatible. An outline of the major electro-optical performance characteristics of the device is shown in Table 1. detailed description of the device, including environmental performance and parameter test methods can be found in SCS-516. In order to provide for a high degree of fiber optic system integrity through the use of redundancy, the injection laser diode has been designed to consist of a triad of discrete lasing elements contained within a single crystal of semiconductor material. This construction will be referred to as "monolithic triple stripe geometry" throughout this report.

#### 2.2 Device Structure

To achieve the electro-optical characteristics outlined in Table 1 , the narrow cavity (<.5µm) GaAs-GaAlAs

Table 1 Electro-optical Performance Characteristics of the Injection Laser Diode for Fiber Optic Communications.

	Min.	Max.	Units
Optical Stripe Width	-	25	μ <b>m</b>
Stripe Spacing	120	130	μ <b>m</b>
Peak Output Power	200	-	mW
Average Output Power per Stripe	6.3	7.0	m <b>W</b>
Peak Wavelength	800	830	nın
Beam Divergence Parallel to Junction	-	15	degrees
Beam Divergence Perpendicular to Junction	-	40	degrees

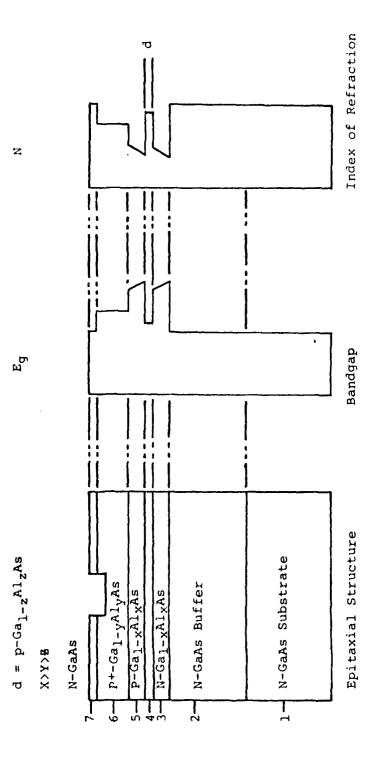
#### Operating Conditions

Ip = 3A max.
Vf = 2.0V max. @ 3A.
Ta = 25°C
tp = 10 nsec
DF = 10%

employed in conjunction with Laser Diode Laboratories' unique stripe geometry current isolation technique.

Devices of this structure have demonstrated low threshold current density (<1KA/cm²), high differential quantum efficiency (>50%), fast rise time (<200 psec), and sufficiently good beam characteristics to satisfy the requirements of most fiber optic systems applications. A schematic diagram of the structure is shown in Figure 1 along with the bandgap, Eg, and index of refraction, n, profiles perpendicular to the plane of the P/N junction.

The substrate, region 1, is n-type GaAs doped with Si to 2 x 10<sup>18</sup>, with EPD <1K/cm<sup>2</sup>. Existing dislocation networks and substrate surface imperfections are terminated by the growth of at least one n-type GaAs buffer layer, region 2, doped with Te to 2 x 10<sup>18</sup>. Regions 3 and 5 are n-type and p-type GaAlAs respectively. These two layers confine light generated by the injection and recombination of carriers in the active region 3, a p-type GaAlAs layer (Si, 1 x 10<sup>18</sup>). Light is confined to the waveguide formed by regions 3 and 5 by virtue of the slight decrease in index of refraction at their boundaries with the lower bandgap active layer. The peak emission wavelength of the laser is controlled by the bandgap of the active region, which in turn is a function of the aluminum



Schematic Representation of the Epitaxial Structure for Fabrication of Stripe Geometry Double Heterojunction Injection Laser Diodes.

concentration of this layer. In this case, 8% aluminum in the active region corresponds to approximately 820 nm peak emission wavelength. In order to obtain the low threshold current densities required for high duty cycle operation and for satisfactory high temperature performance, the recombination volume, hence the active region thickness must be kept small. In the case of CW injection lasers with Jth typically  $\langle 1.5 \text{KA/cm}^2, 'd' \text{ is normally 0.3 to 0.4 } \mu\text{m.}$ Region 6 functions as a contact cap with aluminum incorporated in this p-type Ge doped layer to minimize lateral current flow by increasing its resistivity. Stripe geometry fabrication permits high duty cycle and room temperature CW operation by limiting the lasing region of the active layer to only a small portion of the junction width. This allows heat generated in the 25 µm lasing region beneath the contact stripe to be dissipated throughout the entire bulk of the laser diode pellet. The topmost region 7 consists of lightly doped n-type GaAs. Following photolithographic definition of the contact stripe, 15 to 20 µm wide channels are etched through this current blocking layer. Under conditions of forward bias, current is restricted to flow through the active region only beneath the etched channel. Elsewhere, because the p/n junction formed by interface between regions 6 and 7 is backbiased, the cavity remains unpumped.

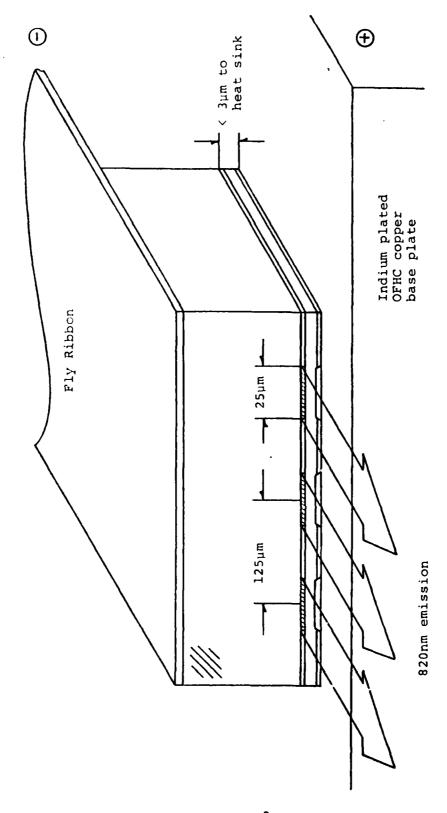
Details of the epitaxial synthesis and wafer processing for monolithic stripe geometry fabrication will be discussed in Section III.

#### 2.3 Array Configuration.

The requirements of SCS-516 dictate the array configuration for the monolithic triple stripe geometry injection laser diode. Figure 2 illustrates the main features of the diode chip. The diode essentially consists of a triad of discrete lasing elements embedded in a single chip of epitaxial GaAs-GaAlAs material. Each element has a maximum optical source size of 25 µm and the elements are spaced at 125  $\mu m$  intervals to facilitate coupling of each individual element to a triple fiber optic ribbon cable. Monolithic construction is preferred because the high degree of dimensional and compositional uniformity inherent in the heteroepitaxial process guarantees optimum uniformity of electro-optical parameters among the three discrete lasing elements. In addition, the high degree of uniformity provides perfect geometrical alignment of the elements relative to each other. Fabrication of the monolithic triple stripe geometry array from epitaxially synthesized wafers is discussed in detail in Section III.

#### 2.4 Package Requirements.

During the first quarter of the program, several modifications to the package outline were requested



Monolithic Triple Stripe Geometry Laser Diode Module Configuration

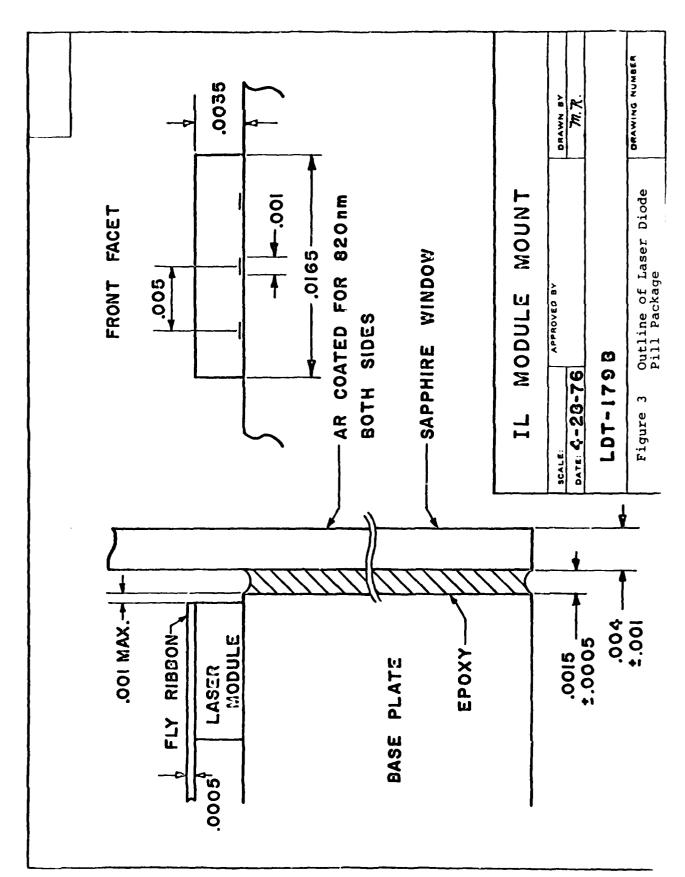
design. These modifications to the proposed package configuration involved increasing the height of the pill package base to better facilitate coupling to the fiber cable end ferrule. Also, the overall height was adjusted to allow the use of square optical windows in production. Figure 3 shows the modified package outline drawing with tolerances. A detail drawing showing the laser module mounting position and orientation within the pill package is given in Figure 4. Final configuration of the package parts and a detailed description of their assembly is given in Section III.

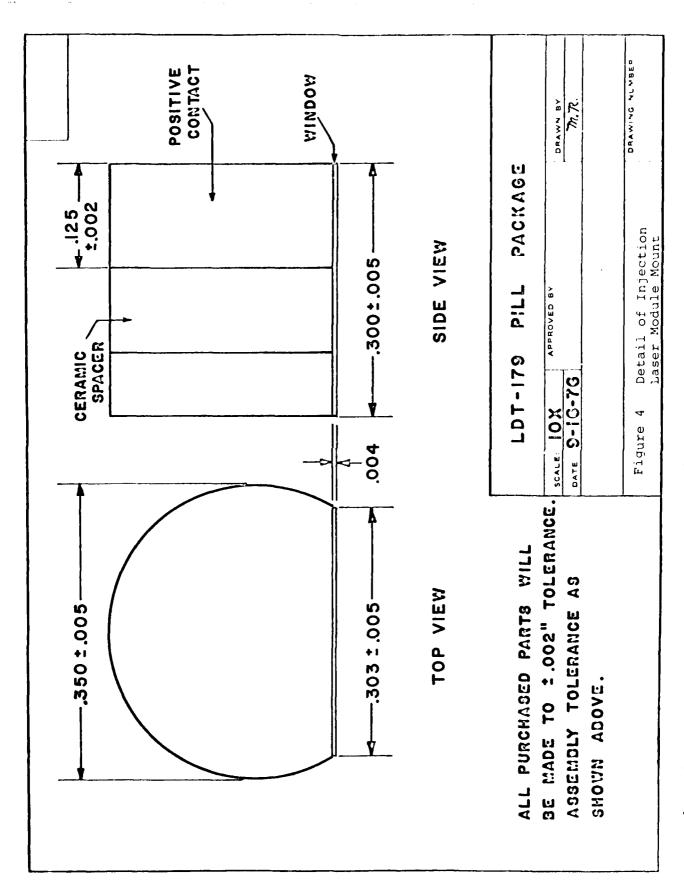
#### SECTION III

#### MANUFACTURING METHODS AND TECHNOLOGY ENGINEERING

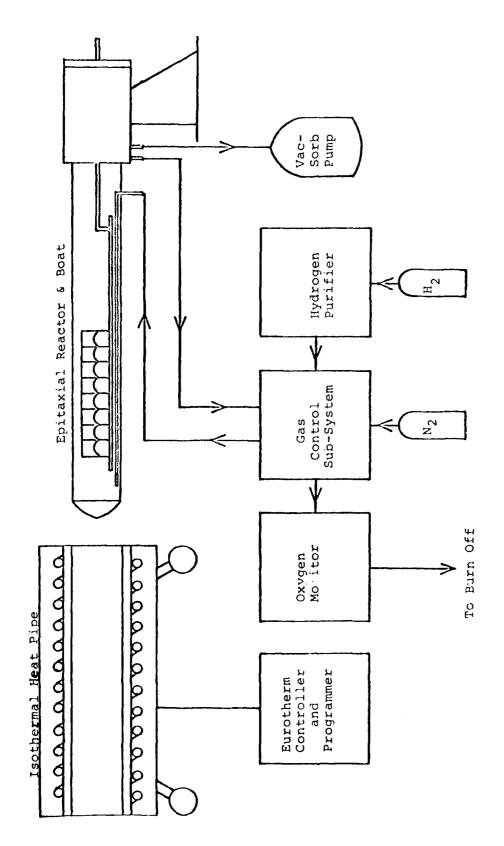
- 3.1 Materials Technology.
- 3.1.1 Synthesis of Device Structure via LPE.
- 3.1.1.1 Liquid Phase Epitaxial System.

Liquid phase epitaxy is a complex process in which single crystal layers of semiconductor material are deposited on a single crystal substrate of lattice matched material by precisely controlled cooling of a saturated solution in contact with the substrate. In the case of hetero-epitaxial synthesis of GaAs and GaAlAs layers for laser fabrication, gallium (Ga) is the preferred solvent and the substrate is normally high quality, low Etch Pit Density, (100)GaAs.





Crystal growth of these structures takes place at temperatures ranging between 750°C and 900°C and must be performed in an inert or reducing atmosphere to avoid the highly detrimental effects of oxygen contamination. The properly designed LPE reactor and support systems must satisfy several criteria in order to yield epitaxial wafers suitable for fabricating monolithic triple stripe geometry laser structures. These criteria are dictated by the uniformity, reliability, and produceability requirements of semiconductor optoelectronic components for volume commercial manufacture. Maximum surface area, layer thickness uniformity, compositional uniformity, and minimum defect density are required. In addition, the as-grown surface morphology of the terminal layer must be compatible with photolithographic processing for the definition and patterning of stripe geometry contacts. Figure 5 shows a block diagram of the epitaxial system in use at Laser Diode Laboratories. This system incorporates several features which have resulted in the optimization of the liquid phase process: Isothermal Heat Pipe Furnace - The sodium filled isothermal liner elimintates all vertical and horizontal temperature gradients and, hence provides uniform deposition rates over the entire surface of the substrate. The isothermal liner also allows the use of larger epitaxial boats, therefore, larger epitaxial

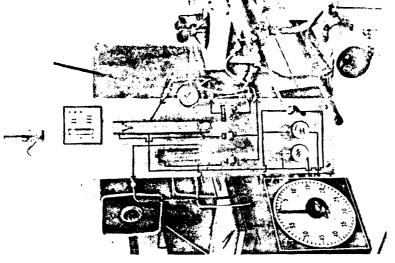


Block Diagram of Liquid Phase Epitaxial Systems Currently in Use at Laser Diode Laboratories.

wafers can be synthesized or more complex structures grown.

Vac Sorb Pump - The use of a molecular sieve prior to
the start of the run completely removes all traces of
oxygen from the growth ambient without the risk of
organic contamination.

Oxygen Monitor - The use of a fuel cell apparatus in the output stream of the system allows continuous monitoring of the O<sub>2</sub> content of the system both prior to and during epitaxial synthesis. The apparatus assures system integrity resulting in reproducible growth rates, alloy composition, and defect free growth by preventing the formation of Al<sub>2</sub>O<sub>3</sub> in the melt. During the first quarter of the MMTE program, several improvements were made in the design of the epitaxial reactor. Noteable among these improvements were the design and construction of new end cap apparatus shown in the photograph of Figure 6a. The new design can support higher vacuum, and operates with lower background 02 levels than could be obtained previously. The optimized design now permits evacuation of the growth tube down to 80 microns and a steady state 02 concentration of 0.1 ppm in the H2 carrier gas. addition, an improved gas supply sub-system has been designed for easier use by production personnel and is shown in the photograph of Figure 6b. A schematic indicating its operation is shown in Figure 7. In addition to obtaining optimum system performance through improved design concepts, the design and construction of



Ď.

/

Figure 6

Photograph of Liquid Phase Epitaxial Reactors at Laser Diode Laboratories.

Figure 7 Schematic Diagram of Gas Control Subsystem

the epitaxial boat is crucial to obtaining high quality hetero-epitaxial material. The ultra high purity, high density graphite boat is shown in the photograph of Figure 8. The eight bin boat utilizes a built-in indexing mechanism for accurate positioning of the substrate in each bin. Also an extra bin is employed to remove excess gallium which may adhere to the surface of the wafer as it is removed from the final melt.

Together, the modified epitaxial reactor and epitaxial boat allow the generation of double heterojunction structures in a manufacturing environment for the volume production of monolithic triple stripe geometry injection lasers.

### 3.1.1.2 Growth Process for the Synthesis of the Double Heterojunction Structure.

Epitaxial synthesis of the double heterojunction structure is accomplished according to the sequence of events outlined in the flow chart of Figure 9. Table 2 lists the melt compositions for the growth of the double heterojunction structure used in the fabrication of the monolithic triple stripe geometry laser diode. After the appropriate melt ingredients, gallium (Ga) charges, and polycrystalline source wafers, have been loaded into consecutive growth bins, the single crystal (100) GaAs substrate is placed into the slider well of the high purity graphite boat (refer to Figure 8 ). A graphite cover plate is employed to eliminate surface

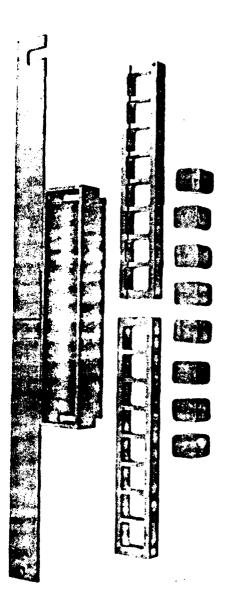


Figure 8 Photograph of Eight Bin Ultra High Purity Graphite Epitaxial Boat.

- 18 -

15.

Figure 9 Sequence of Operations for Liquid Phase Epitaxial Synthesis. - Weigh Melt Ingredients. Prepare Clean & Etch Source Wafers. Materials Clean & Etch Substrate. Load Solid Components. Load Load Ga Changes. Boat · Load Source Wafer. · Place Graphite Blocks. Place Boat Position Boat Against Backstop. in Growth Engage Control Rod in Slider. Chamber Seal End Cap. Evacuate Evacuate via Vac Sorb. and Backfill with H2. Purge Chamber Purge until O2 <1 ppm. Saturate Roll Furnace into Growth Position. Melts Equilibrate to 850°C. Soak 1 hour. Deposit Engage Cooling Ramp. Layers Advance Control Rod According to Growth Sequence. Roll Furnace to Idle Position. Terminate Engage Cooling Fan. Run Purge with N2. Remove Boat

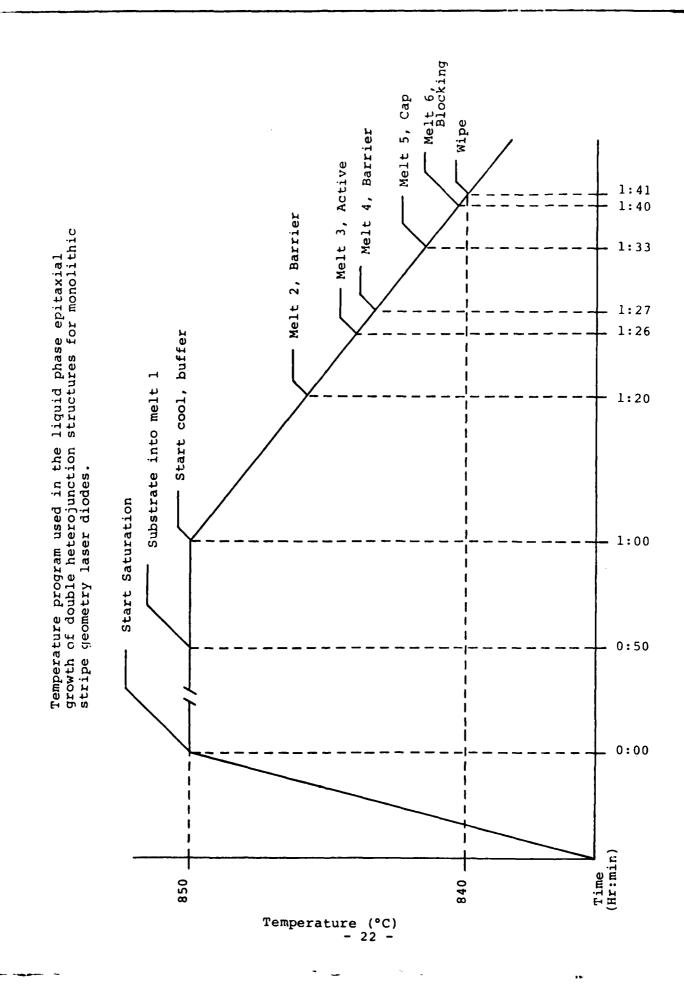
 $\label{eq:Table 2} \mbox{Melt Compositions for Double Heterojunction Epitaxial Synthesis.}$ 

Layer	*GaAs	<u>Ga</u>	<u>A1</u>	<u>Te</u>	<u>Si</u>	<u>Ge</u>
1	0.6K	5.0K	~	1.0	-	-
2	0.6K	5.0K	6.0	1.0	-	-
3	0.6K	5.0K	1.0	-	15.0	-
4	0.6K	5.0K	6.0	-	-	0.1K
5	0.6K	5.0K	0.2	-	-	0.5K
6	0.6K	5.0K	_	_	-	-

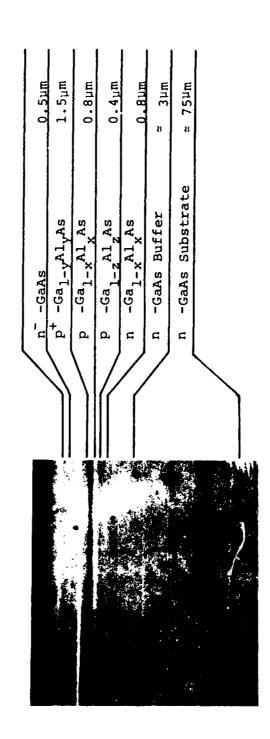
<sup>\*</sup> Polycrystalline source wafers.

<sup>\*\*</sup> Weights in mg.

dissociation of the substrate during equilibration. The boat is then loaded into the quartz growth tube and the system is evacuated by means of the Vac-Sorb pump. Following a short H2 purge, the system is brought up to the starting temperature of 850°C by rolling the isothermal liner into the growth position. Melt saturation is accomplished during a one hour soak at 850°C during which time enough GaAs is dissolved from the source wafers in order to exactly saturate each melt. This recently developed self-saturation scheme has simplified the growth procedure by eliminating the need for careful preweighing of GaAs for each melt. In addition, higher quality layers and increased run to run layer thickness reproduceability have been achieved with this technique. Once saturation has been achieved, epitaxial synthesis procedes accoring to the time temperature program shown in Figure 10. Individual layers are epitaxially deposited by advancing the substrate through the consecutive growth bins for a precisely controlled time interval. Because growth rates for the various melts are well defined for a fixed starting temperature and cooling rate, layer thickness can be accurately and reproduceably controlled using this technique. A cleaved and etched cross section of a typical wafer synthesized for use in the fabrication of the monolithic triple geometry laser diodes is shown in Figure 11. In addition to the excellent dimensional and compositional uniformity of the layers, the surface



Photograph of typical double heterojunction structure required for the manufacture of monolithic stripe geometry injection laser diodes.



morphology of the heteroepitaxial wafer is characterized by freedom from pit type defects and exhibits a high degree of flatness compatible with the photolithographic processing steps required for the application of stripe geometry to the wafer surface. Photomicrographs of the surface are shown in Figure 12.

# 3.1.2 Wafer Processing for Monolithic Triple Stripe Geometry Module Fabrication.

Following liquid phase epitaxial synthesis, the wafer must be processed into individual triple stripe geometry modules. The processing steps required for the fabrication of the modules, are illustrated schematically in the process flow chart, Figure 13. After epitaxial synthesis of the multiheterojunction structure, the wafer undergoes a preprocess cleaning to remove residual Ga from the surface, Figure 13 (a). Approximately .050" of material is cleaved from all four edges creating mutually perpendicular (110) reference planes to be used for channel stripe alignment. The proper <110> alignment plane must be identified prior to epitaxial growth since a V-shaped channel cross section is desired. This is normally accomplished by defining channels on a sample substrate and observing the channels' cross section. Once identification of the <110> has been accomplished, the proper alignment plane is known for all substrates cut from a given ingot.

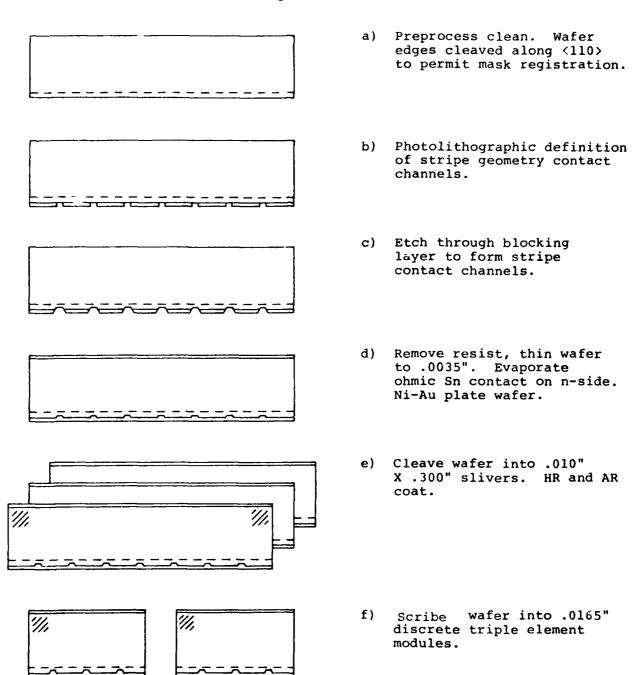
Photolithographic definition of the stripe contact





- 25 -

Process flow diagram for the fabrication of monolithic stripe geometry injection laser arrays.



channels is accomplished by aligning the mask reference with the proper <110> direction as indicated schematically in Figure 13 (b).

Photolithographic definition is followed by a 3:1:1, Methanol:Phosphoric: Hydrogen Peroxide etch which removes the n-GaAs blocking layer forming an array of etched 20 µm wide contact channels in the p-GaAlAs contact cap. Parallel contact channels are spaced on .005" centers over the entire surface of the epitaxial wafer as shown in Figure 13 (c).

After removal of the masking resist, the epitaxial wafer is thinned to .0035" and Sn ohmic contacts are evaporated over the n-side of the thinned wafer, Figure 13 (d).

Ni-Au electroplated contacts are applied to both sides of the wafer forming ohmic contact to the exposed p-GaAlAs contact cap in the stripe channels.

Mirror facets are formed by cleaving the epitaxial wafer in the slivers approximately .010" by .300" as indicated schematically in Figure 13 (e).

Cleaving is accomplished with the aid of a diamond scribing apparatus shown in the photograph of Figure 14. The cavity length is accurately and reproduceably controlled by the micro-index control on the vacuum chuck of the scriber.

Reflective coating of the back facet of each sliver is accomplished by vacuum deposition of successive films of SiO (2000Å), Cr (50Å), Au (4000Å), Cr (100Å), and



Figure 14 Scribing Apparatus for Cleaving Epitaxial Wafer into Slivers.

Sio (300Å).

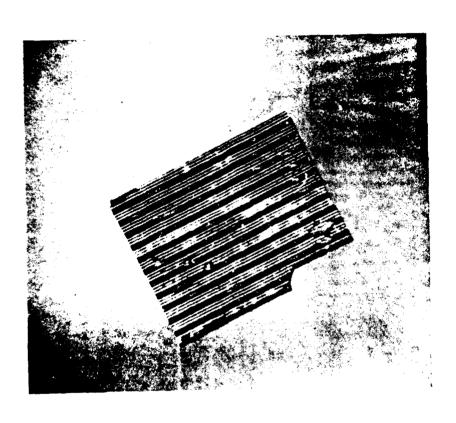
Finally, in Figure 13 (f), the individual slivers are cut on .025" centers with a ganged wire saw having a .0035" kerf.

Figure 15 shows an epitaxial wafer to which triple stripe geometry contacts have been applied. Figure 16 shows individual modules after they have been cleaved, coated, and cut to size ready for assembly onto the pill package.

### 3.2 Packaging Technology.

# 3.2.1 Package Design.

During the first quarter of the program, finalization of the package design and procurement of pill package blanks for fabrication of the first engineering samples was carried out. The pill package blank consists of a brass negative electrode, an Al<sub>2</sub>O<sub>3</sub> ceramic spacer, and an OFHC copper positive electrode which serves as the primary heat sink for the monolithic triple stripe geometry injection laser diode module. These three major components are bonded together through the use of a high temperature alloying technique and are purchased from the supplier as a complete assembly. Engineering drawings for the piece parts are given in Figures 17, 18, and 19. In addition to the package blank, the optical window along with its epoxy preform for attachment make up the remainder of the package parts. Parts drawings for these two components



Photograph of Triple Stripe Geometry Applied to Surface of an Epitaxial Wafer.

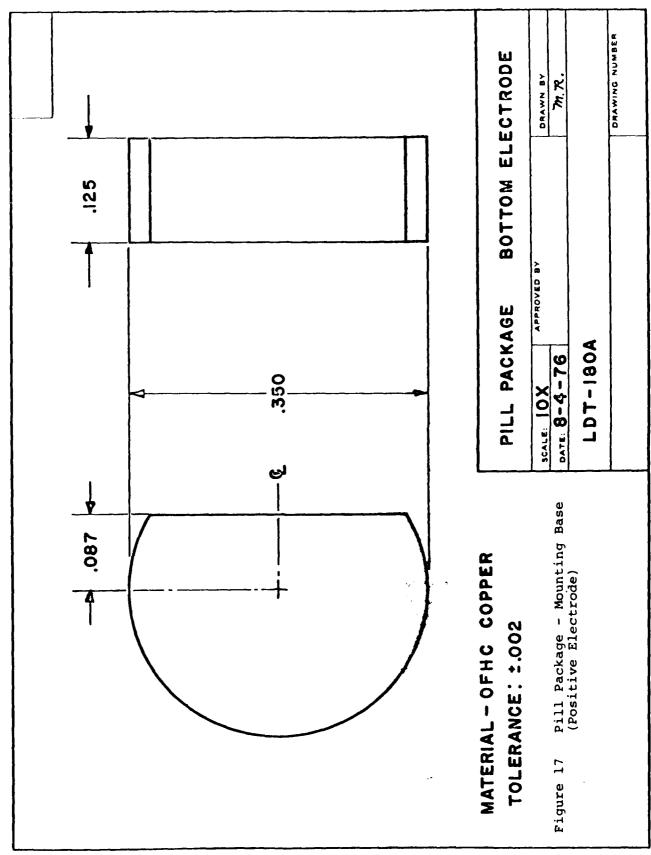
Figure 15

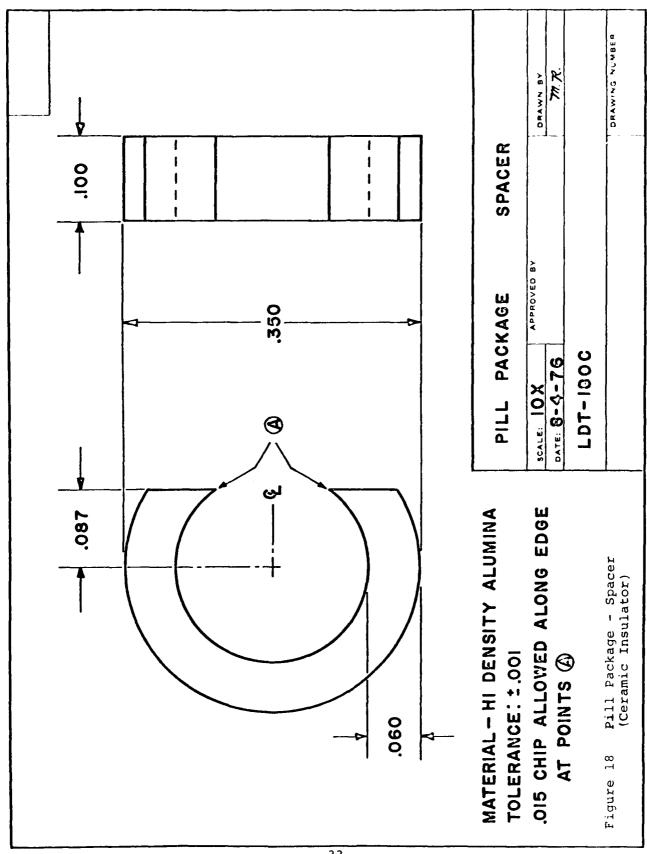
- 30 -

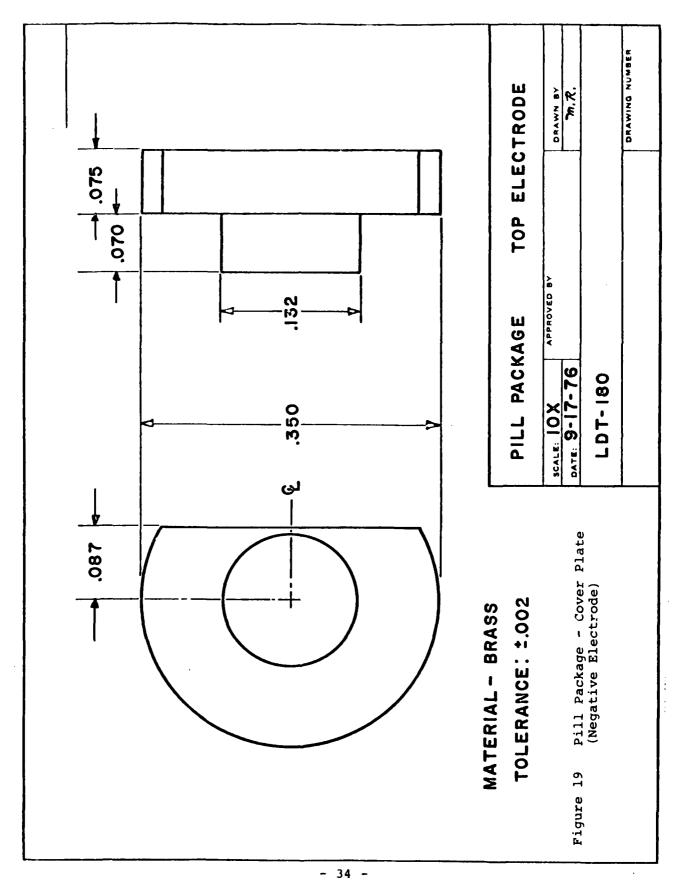


Photograph of Individual Triple Element Modules.

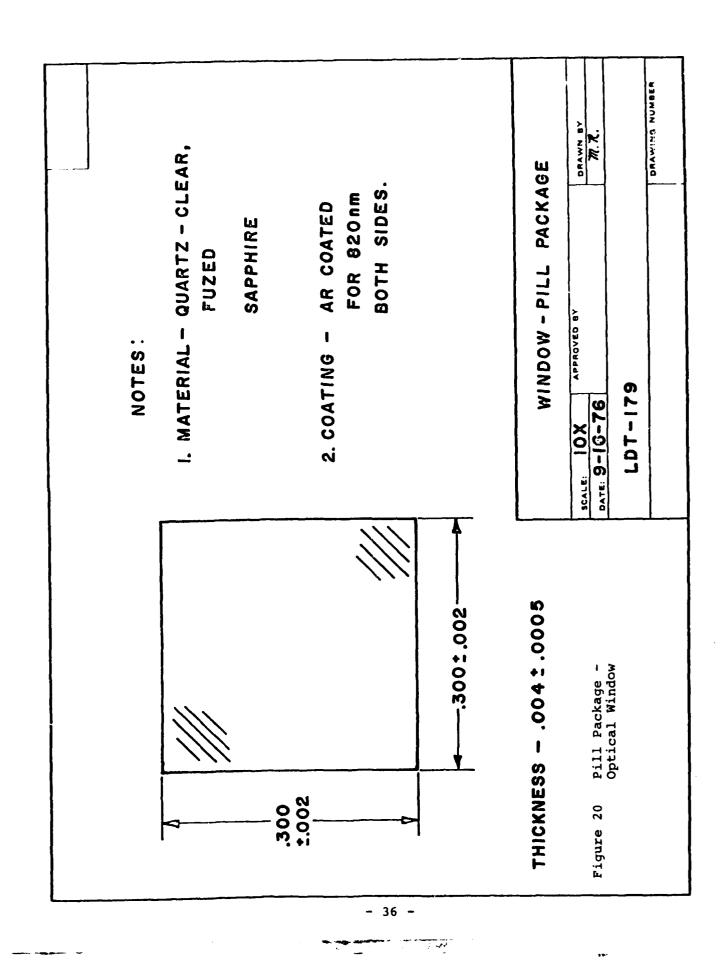
Figure 16

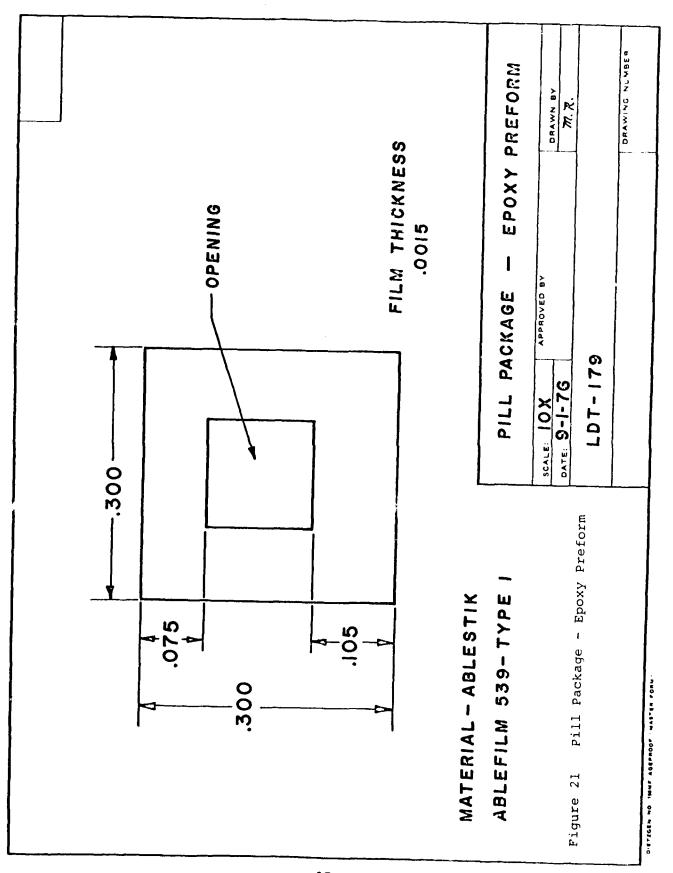


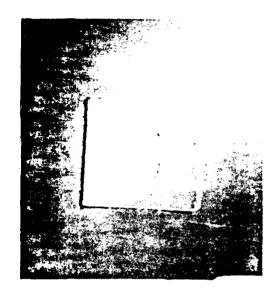


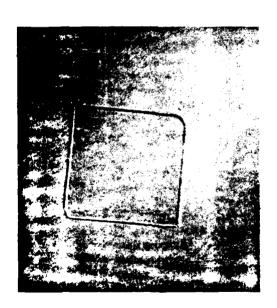


are shown in Figures 20 and 21 and photographs of the window and preform are shown in Figure 22 (a) and (b). The epoxy utilized in this assembly is Ablestik type 539 and is supplied as a stamped preform. Type 539 consists of a non-frozen epoxy applied to both sides of a thin mylar film carrier. Preforms of this type are available in 0.0005" increments up to 0.003" thick. The epoxy is tack free prior to curing and can be stored at 25°C for an indefinite period of time. Curing is accomplished by heating to 110°C for two hours and results in an extremely uniform bond line with a shear strength of 3000 psi. Because extremely thin films of epoxy are applied to the mylar carrier, deformation of the preform during cure is minimized. This feature together with the inherent uniformity of the mylar film carrier makes this an ideal material for the attachment of the optical window to the laser diode pill package. In a parallel effort, the use of a similar mylar preform as an electrical insulator to be employed in place of the ceramic was actively being investigated. advantages to using epoxy preforms for this application have become evident to date. In order to obtain a perfectly flat mounting surface for the 0.004" thick optical window, the front face of the pill package blank must be lapped prior to use. The presence of the ceramic insulator introduces some degree of difficulty in this step owing to the difference in hardness between







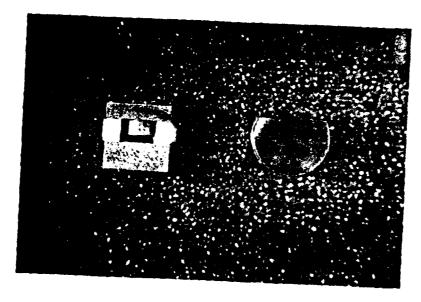


Photograph of Optical Window and Epoxy Preform.

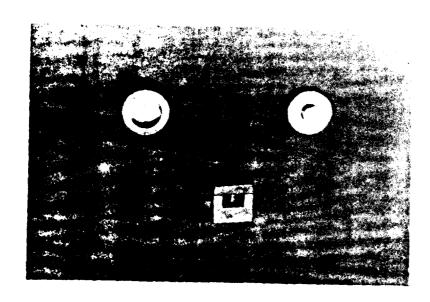
Figure 22

 ${\rm Al}_2{\rm O}_3$  and copper. Although perfectly flat mounting faces can be obtained, the lapping must be done carefully to prevent rounding. When the blank is designed for use with an epoxy-mylar insulator, the lapping accomplished with much less difficulty and with a minimum of material removal. In addition, the copper-mylar blank is about one third as costly as its copper coramic counterpart. Photographs of both types of pill package blanks are shown in Figure 23 (a) and (b).

Experiments have been performed and indicate that packages assembled from all metal parts, with the epoxy preform, can be machined and lapped to provide a smooth surface for window attachment. With this smooth surface, it has been possible to attach the window with a low viscosity UV curing epoxy which allows for a thin epoxy layer on the order of a half mil thickness. This method is preferred to the preform method of window attachment as it provides effective sealing of the window without pressure and temperature, and a cure time of only 15 seconds.



a. Cu-Ceramic Blank. (2.5x)



b. Cu-Mylar Blank. (1.5x)

Figure 23 Pill Package Blanks

### 3.2.2 ASSEMBLY TECHNIQUES

A blow-up of the basic laser diode pill package is illustrated in Figure 24. The parts are assembled by aligning the upper and lower copper parts with the preform in between, applying moderate pressure to the parts while curing at 110 °C for 2 hours. In practice a number of units are assembled and placed in a "vee" shaped fixture which serves to keep the parts aligned while pressure is applied. The fixture is shown in Figure 25. After curing of the epoxy preform, the package is machined to provide the flat window surface as shown in Figure ". To complete the surface finish for window attachment the machined packages are placed in a rubber pad, such that the flat surface can be placed in contact with a lapping plate. The rubber pad is shown in Figure 27 and the lapping machine in Figure 28. When the texture of the flat window surface change to a mat finish, the lapping is complete. The pill package blanks are individually inspected and then electroless nickel and gold plated. Next a 2 mil gold fly wire is soldered to the upper electrode center post with 60/40 pb/Sn solder. The mounting area on the bottom electrode is tinned with Indium, the diode chip placed just back of the edge and

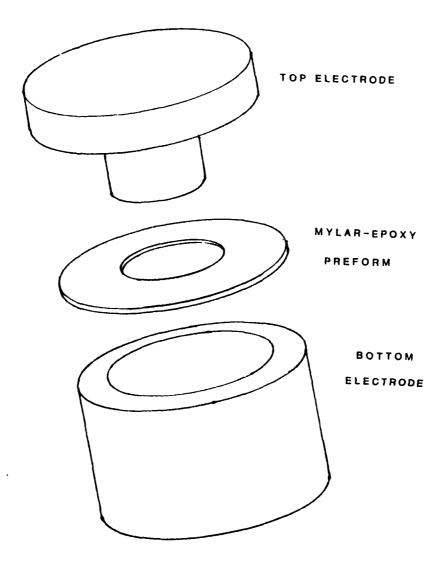


Figure 24 - PILL PACKAGE COMPONENTS

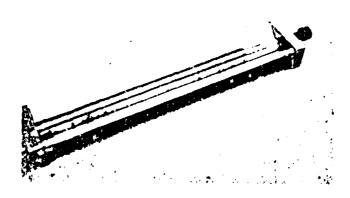


Figure 25- Bonding Fixture with Packages Clamped for Bonding.

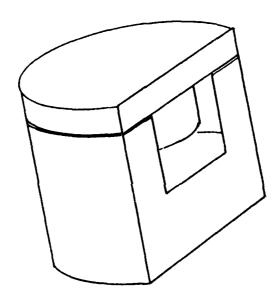
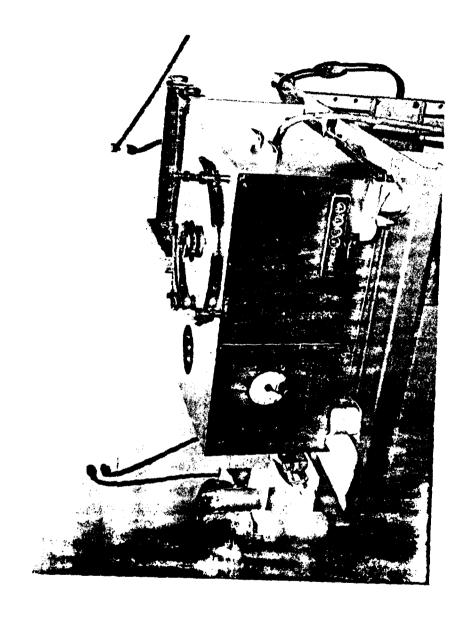


Figure 26.

PILL PACKAGE ASSEMBLED AND MILLED



Figure 27.
Rubber Lapping Pad.



Photograph of Lapping Apparatus used to Obtain Flat Window Mating Face, Figure 28

soldered in place. An Indium preform is placed on top of the chip and the free end of the wire of the top electrode shaped to press into the preform. The assembly is reheated to the Indium melting point allowing the preform to melt and make connection to the top of the chip. The P-side of the chip is soldered to the bottom electrode. All the above soldering is performed on a carbon strip type heater. The packaged laser can be tested amd burned in at this point in the assembly. After testing, the window is attached to the package by placing a thin bead of UV epoxy near the outer edge of the flat surface, placing the window on the bead and applying light pressure to the window to cause the epoxy to spread over the flat mounting surface. The epoxy can be observed to spread through the window and can be controlled so as not to flow onto the laser face. After a 2 second cure under a UV lamp, excess epoxy that has flowed around the outside of the package is removed with a solvent. A final cure of 15 seconds secures and seals the window. The window attachment sequence is carried out in a nitrogen dry box to minimize moisture content within the sealed package. The flow chart in Figure 29 shows the sequential steps in the package assembly and diode mounting. The final package configuration is shown in Figure 30 .

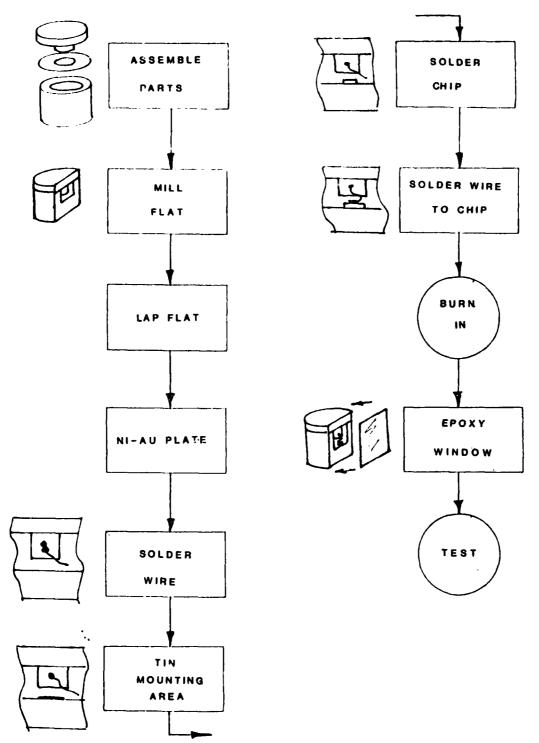
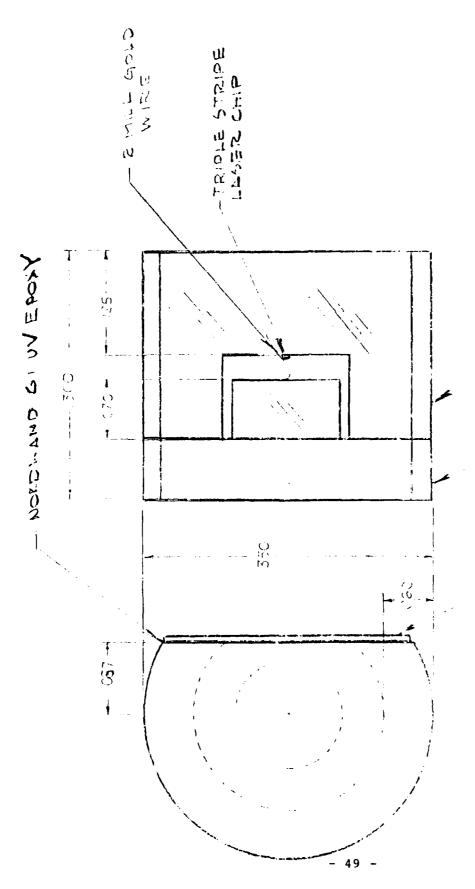


Figure 29 PILL PACKAGE-LASER ASSEMBLY FLOW CHART



母のなどの明明 大のいのかり

THE PROPERTY OF THE PROPERTY O

Figure 30 - Completed Package Configuration

# 3.3 DEVICE EVALUATION AND TESTING

#### 3.3.1 TEST EQUIPMENT

A 10 MHZ pulser capable of delivering drive currents up to 3.0 amperes at a duty factor of 10%, forms the basis for all the electro-optical measurements carried out on the devices. The circuit schematic is shown in Figure 31. The driver consists of two microwave transistors, CD1194 and CD1979, which are cascaded for high current gain. The pulser is triggered with a positive pulse or high logic level at the base of CD1194 through a decoupling capacitor. The diode FD600 is used for protection of the CD1194 from reverse  $V_{\mbox{\footnotesize{BE}}}$  voltages. The current through the laser is controlled by the 50 ohm potentiometer in the emitter circuit of CD1194. The coils in the supply buss are used for high frequency isolation and provide quick recharge speeds for the capacitor in the collector circuits. The pulser test set assembly is shown in Figure 32.

The Burn-In and Life Test Rack uses a different circuit which is shown schematically in Figure 33. The driver consists of two descrete components. A microwave transistor, CTC D3-28  $(Q_2)$ , acts as a pre-driver for Siliconix VMOS FET 2N6657  $(9_3)$ , which is capable of switching

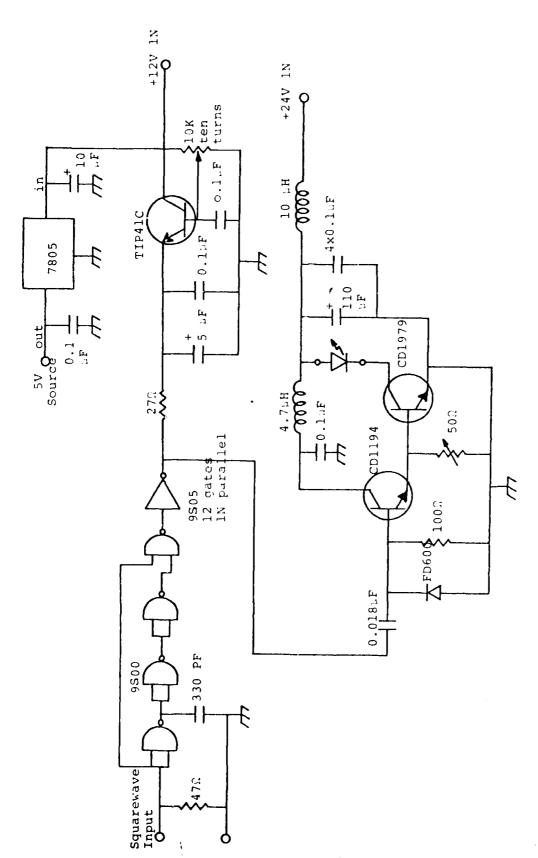


Figure 31. Transistor 10 ns Pulser.

ij.

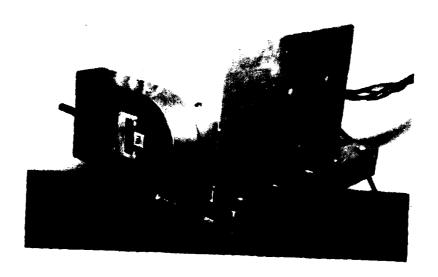


Figure 32 -Transistor Test Pulser Assembly.

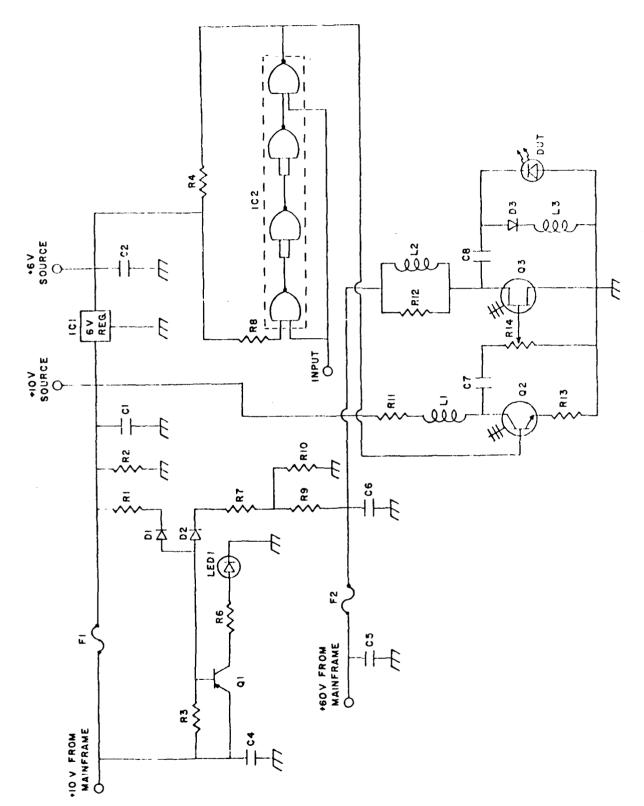
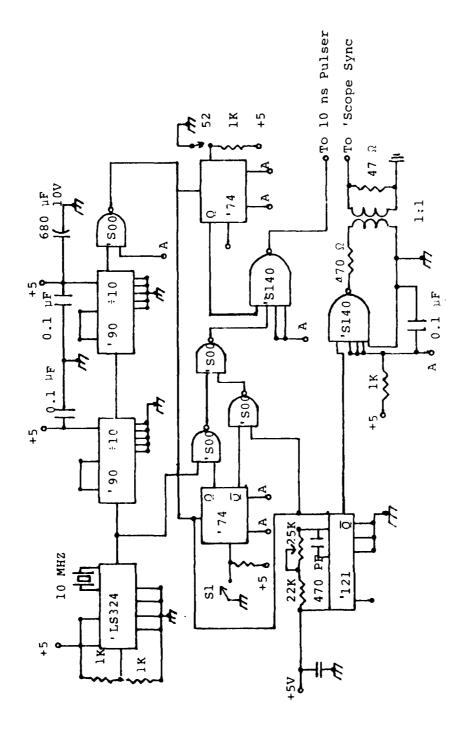


Figure 33 - Revised 10 MHC 1.D Driver (Single (osition) Circuit Schematic.

in the nano-second range. The circuit is tuned for 10 ns pulse width operation. The input pulse must also have a 10 ns trigger pulse width with a 90% recharge time.

The pulse sequence is started when a high TTL logic level is present at the base of  $\mathrm{Q}_2$  turning it "ON". The gate of  $\mathrm{Q}_3$  is capacitively switched "OFF" by C7 through R14. The coil L1 begins storing energy from the Collector Current of  $\mathrm{Q}_2$ . In the drain circuit of  $\mathrm{Q}_3$ , the coil L2 and capacitor C8 is charging through the 60V supply, diode D8 and Coil L3. The DUT is back biased at this point. After 90% of the cycle, the input logic level goes low and  $\mathrm{Q}_2$  turns "OFF". The coil L1 quickly pumps current through C7 which previosuly was discharged and depending on the setting of R14, turns  $\mathrm{Q}_3$  "ON". The drain current comes from the DUT through C8 which was charged. The current through L3 is checked by D3. The discharge time of C8 will control the pulse width through the DUT. The sequence begins again when the TTL input goes high.

Figure 34 shows the schematic circuit for the 10 ns clock. Figure 35 is the circuit for a clock buffer for the multiposition rack. A single position board is shown in Figure 36.



Notes:

1. All Caps 0.1 F Unless Otherwise Noted.

. All Logic 7400 Series TTL.

Figure 34 Clock and Control Circuit for Transistor Pulser.

**-** 55 -

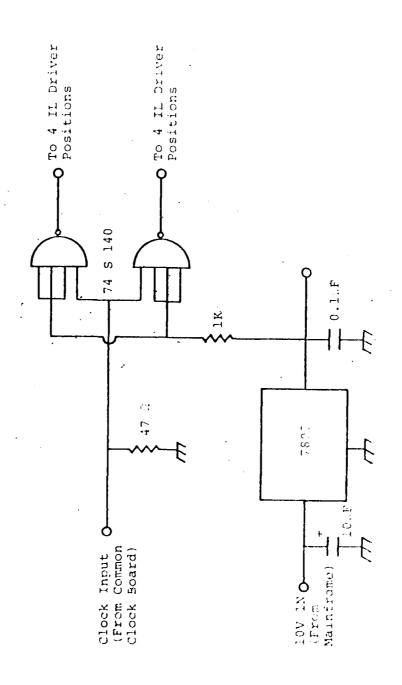
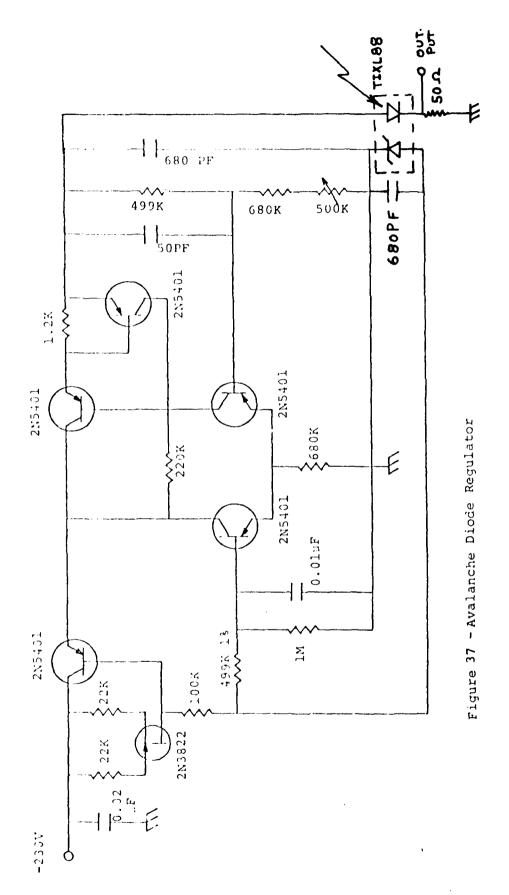


Figure 35, Lonal Glock Buffer for Burn-in Rack.



Figure 36 - Burn-In Position Board with Edge Connector Fingers.



The detector circuit shown in Figure 37 is built around a TIXL88 Avalanche Photodiode/Reference Diode pair that have been manufactured to ensure close matching of both the breakdown voltages and temperature coefficients of the two diodes. The APD power Detector System is shown in Figure 38 indicating the essential features of the power supply and detector head. The internal structure of the detector head shown in Figure 39 depicts the layout of the APD and the diffusion film which allows the small active diode area measure a signal proportioned to the power incident upon the 1.09 cm X 0.394 cm aperture as required by SCS-516. Laser light which is incident on the aperture becomes diffused into an approximately lambertian distribution such that the energy in a relatively small angle is proportional to that which is incident upon the aperture. Since the APD's active diameter is 0.762 mm and it is mounted 79 mm from the diffuser, the solid angle subtended is approximately 1.25 degrees and the approximation is much better than the overall precision of the system. The detector box is mounted to the optical rail using standard fixtures including a vertical vernier which permits accurate positioning of the detector. In use, the detector head aperture is

- 59 -

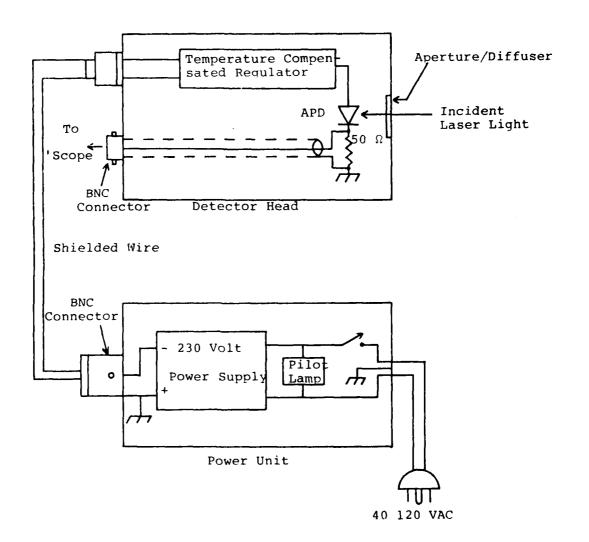


Figure 38 - APD Power Detector System.

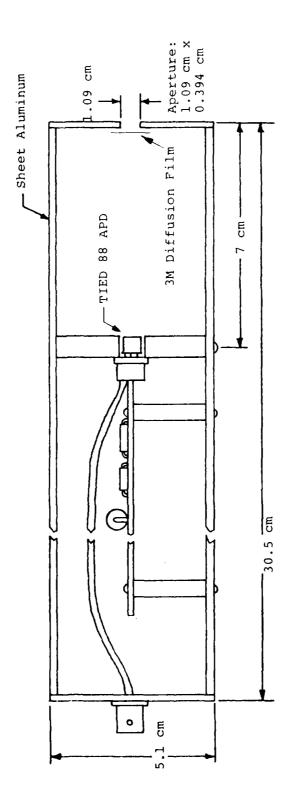


Figure 39 -Internal Structure Power Detector Head.

placed 1.5 cm from the laser to be tested, the power supply is connected and turned on and the detector output is fed to one channel of the sampling oscilloscope. Since the other channel is connected to the current probe in the laser pulser and the 'scope is synchronized to the clock, the oscilloscope trace will, with appropriate calibration factors, read power output vs. drive current.

The far field ("beam pattern") apparatus block diagram is shown in Figure 40. With the 10 ns pulser (Fig 32) mounted atop the goniometer, taking care to locate the laser optical axis on the axis of rotation of the goniometer, the EG&G detector head is located between 65 cm and 75 cm away from the laser (Figure 41) so that its active area subtends a solid angle of less than one degree. The output from the gonimeter drives the XY recorder's X axis and the "chart recorder output" from the EG&G 460 drives the "Y" axis. Once the appropriate scale factors are set up, the head is simply rotated manually (Figure 42) to obtain the desired graph.

Figure 43 shows a similar circuit diagram interfaced with a spectrometer for wavelength and special width measurements.

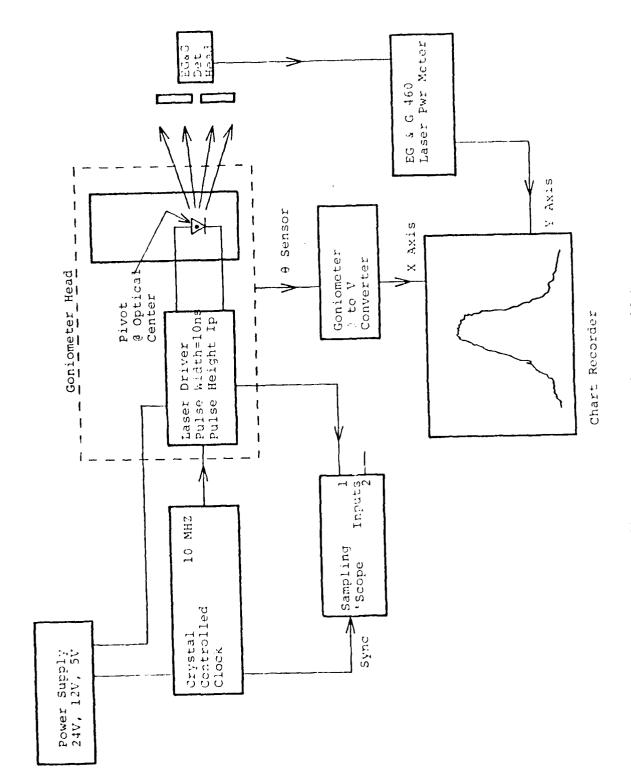


Figure 40 . Measurement of Beam Width.

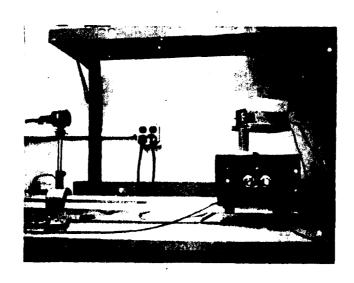


Figure 41 - Photo of EG&G with Pulser on Goniometer on Rail.

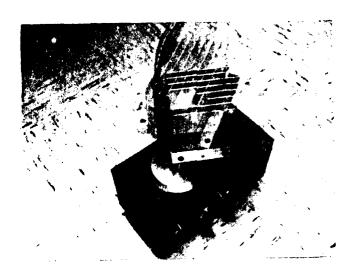


Figure 42 - Double Exposure Illustrating Goniometer Operation.

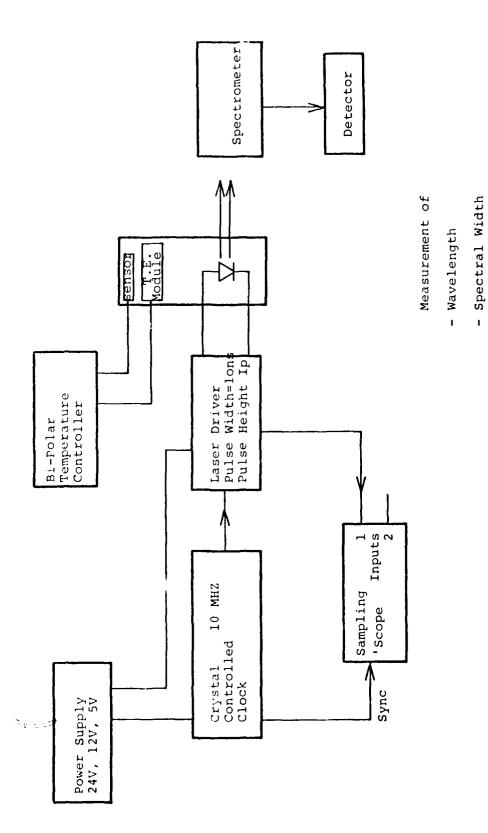


Figure 43

: ;

Figure 44 is a diagram of the stripe width and stripe to stripe uniformity measurement system. With a suitable lens, the triple stripe image is projected on to a screen with a measurement grid as background. This projected image is picked up by a video camera, processed by a video analyser and displayed on a video monitor. Part of the display on the monitor is the intensity pattern which can be gauged for stripe to stripe uniformity. Additionally, the actual stripe images are displayed and gauged against the grid background with the appropriate magnification factor for stripe width and stripe to stripe distance. Figure 45 is a photograph of the video monitor with an actual display. The display illustrates to the left, on the monitor, the intensity of the center stripe. The gridded background is seen with calibration dimensions. Figure 46 shows the block diagram of the  $\mathbf{I}_{\mathbf{D}}$  and peak power measurement equipment. The previously described components are integrated to form the basis for the test set.

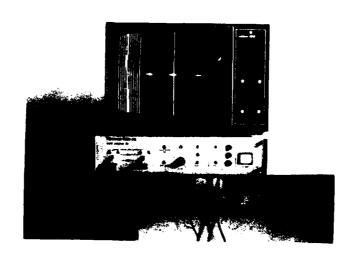


Fig. 45 - Triple Stripe Video Display

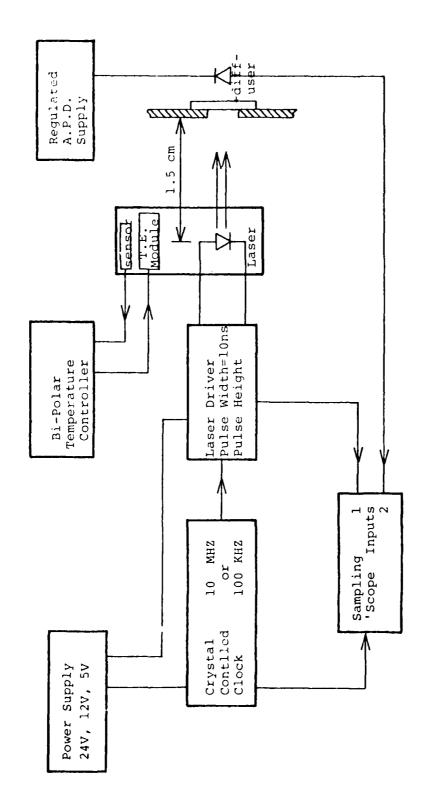


Figure 46. - Measurement of Ip and Peak Power.

## SECTION IV

SUMMARY OF PILOT LINE TEST RESULTS

TESTING CYCLE

TESTING CYCLE CONSISTED OF:

PROCESS CONDITIONING

PRE-BURN-IN ELECTRICAL

Burn-In (168 Hrs.)

POST BURN-IN ELECTRICAL

GROUP A INSPECTION

GROUP B INSPECTION

GROUP C INSPECTION

ENVIRONMENTAL TESTS PERFORMED AT:

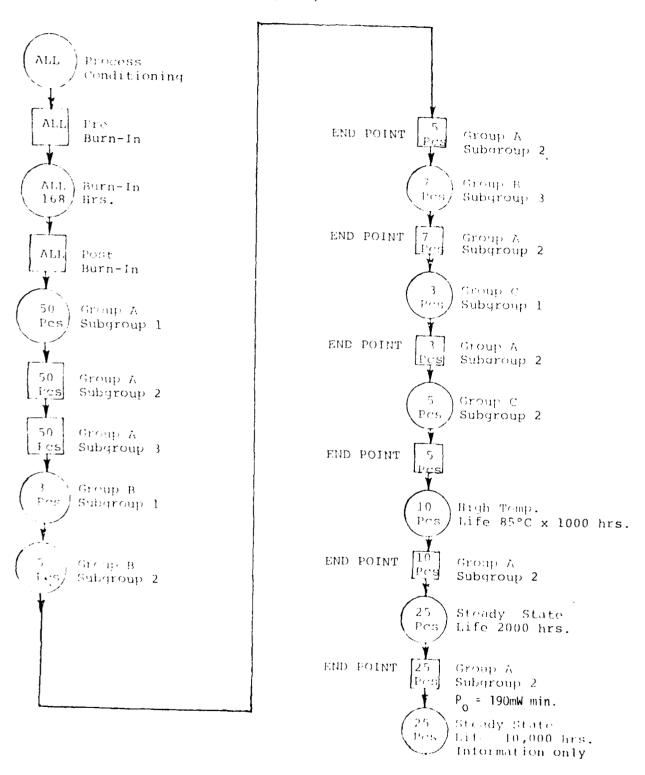
AMERICAN ELECTRONICS LABORATORY
LANSDALE, PA

&

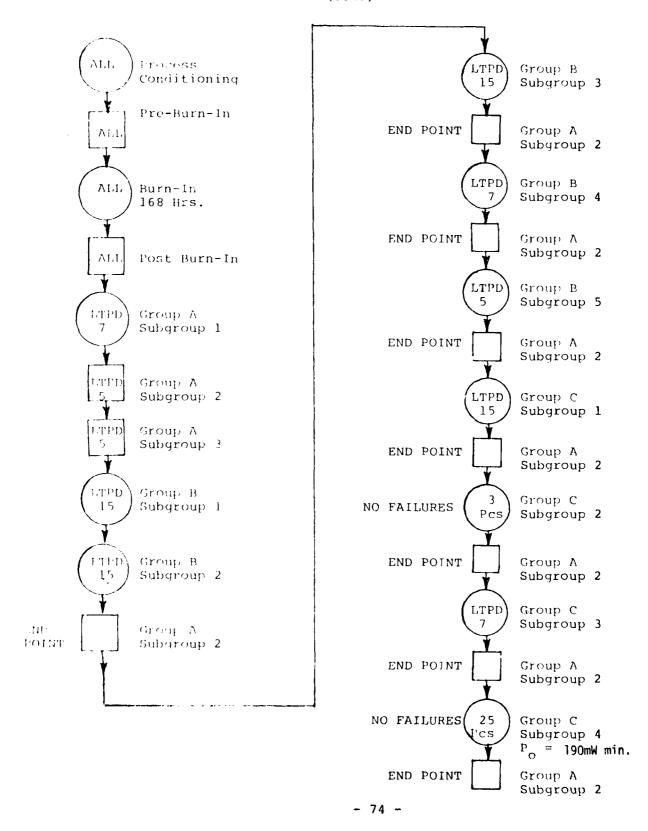
Associated Testing Laboratories
Burlington, MA

# FLOW CHART - FIRST ARTICLE (50 Pcs.)

(0040)



# TLOW CHART - PRODUCTION TESTING (0040)



...

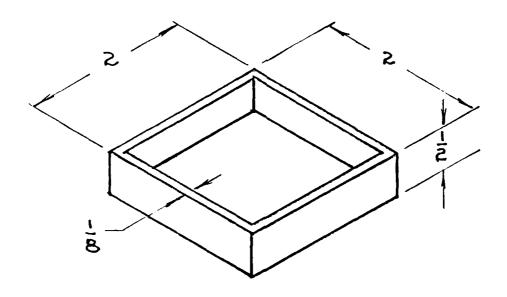
(0040)

# PROCESS CONDITIONING - ALL UNITS

# CONDITIONS

TEST	MIL=STD.	METHOD	REQUIREMENTS	TYP. RES.
High Temperature Life	750	1031	85°C x 48 hrs.	PASS
Thermal Shock	202	107/A	tr=-40°C th=85°C	PASS
Constant Acceleration	750	2006	n 1000 6 directions	PASS
PRE-BURN-IN				
Peak Wavelength	8	800-830 nm	ı	820 nm
Output Power 25°C	200 mw: D	oF=10%: t	=10ns: I <sub>p</sub> =3A max.	21/
BURN-IN	DF=10%: t <sub>p</sub>	=10ns; I <sub>p</sub> =2	А Тур.	
POST BURN-IN		<u>'</u>		
Peak Wavelength	8	300-830nm	∴λ=5% max.	820 nm
Output Power 25°C	200 mw: D	)F-10%: t	=10ns: I=2A Typ.	200 mw

CAVITY LINED WITH HARD RUBBER
DEVICES PLACED WINDOW DOWN ON RUBBER
CAVITY FILLED WITH STEEL SHOT



ACCELERATION FIXTURE

# GROUP A

	CONDITIONS	
TEST	REQUIREMENTS	TYP, RESULTS
SUBGROUP 1		
Visual & Mechanical	MIL-STD-750 Meth. 2071	PASS
Stripe Width	10% DF t <sub>P</sub> =10 ns	_
Triple	75 pm Max.	1
SUBGROUP 2	END POINT TESTS	
Peak Wavelength	815 <u>+</u> 15 nm	820 nm
Peak Pulse Output Power	200mw min. @ 2A Typ.	200 mw
SUBGROUP 3		
Beam Width	At 202mw min. at 1 p	
a) Junction Plane	15°	13 + 2°
b) Perpendicular to Junct.	40°	38 <u>+</u> 2°

# GROUP B

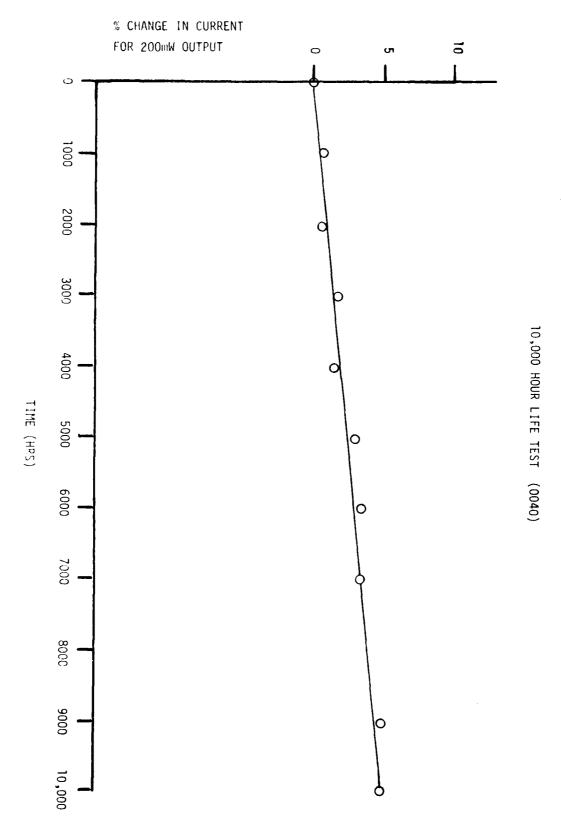
## CONDITIONS

			331.22.21			
TEST	MIL-STD	-1	METHOD_	REQUI	REMENTS	TYP. RES.
SUBGROUP 1	,					
Physical Dimensions	750		2071			PASS
SUBGROUP 2				· · · · · · · · · · · · · · · · · · ·		
Thermal Shock	750		1051	A-10	cycles	PASS
Moisture Resistance	750		1021			PASS
End Point	Group	A -	Subgroup	2		NO CHANGE
SUBGROUP 3						
Shock	750		2016	500g	0.5 ms	PASS
Vibration Fatigue	750		2046	-		PASS
Vibration, V.F.	750		2056	-		PASS
Constant Acc	850		2006	1000	g 6 dir	
Und Point	Group	A -	Subgroup	2		
SUBGROUP 4	<u> </u>					
High Temp. Life	850		1032	82°C	x 340 hrs.	PASS
End Point	Group	A -	Subgroup	2		NO CHANGE
SUBGROUP 5						
Steady State Life (340 Hrs)	750		1027	DF=10 I=2A	)%tp=10ns: Typ.	
End Point	Group	A -	Subgroup	2		200mW @ 2A Typ

For First Article Subgroups 1.2 & 3 Only

# GROUP C

TEST	MIL-STD	METHOD	REQUIREMENT	TYP. RESULTS
SUBGROUP 1				
Thermal Shock	750	1051	Al-25 cycles	PASS
End Point	Group	A Subgro	oup 2	NO CHANGE
SUBGROUP 2				
Solvent Resistance	202	215		PASS
End Point	Group	A Subgro	oup 2	PASS
SUBGROUP 3				
Hign Temp. Life	750	1031	85°C x 1000 hrs	PASS
End Point	Group	A Subgro	oup 2	NO CHANGE
SUBGROUP 4				
Steady-State Life (2000 Hrs.)	750	1026	DF=10%:tp=10ns: I=3 A max.	PASS
End Point		A Subgracept Pa=		200 mw



# SECTION V

# PILOT LINE RATE REPORT

PROCESS	YIELD 8	DEVICES REQ'D	RATE/HR	
Doliver Devices		300		
Final Electrical Test	06	330	48	
Burn-In	100	330		
Pre Burn-In Electrical	63	452	48	
Environmental Testing	100	452		
Attach Window	95	475	52	
Wire Bond to Chip	06	522	20	
Chip Mounting	80	627	20	
Wire Bond to Post	95	658	48	
Package Assembly	85	756	200	

TABLE 8 - PILOT LINE DATES

SECTION VI

MASS PRODUCTION PLAN

	FOR FIRST WEEK'S PRODUCTION
0.	PROGRAM SCREDULE & PROGRESS CHART REVISIONS
QUANTITY	SCHEDULE & PROGRESS BY WEEKS
DESCRIPTION	1 2 3 4 3 3 7 3 9 10 11 12 15 14 15 15 17 18 19 20 31 32 13 23 23 25 25
OF WORK WEST	
Order Package Parts	
Build Burn-In Racks	
Build EPI Furnace	
Grow & Process EPI toChips	
Assemble Packages	
Packages Mount	
Process Condition (Lab)	
Pre Burn-In Thru Final Test	
Group A Tests	
8	
1	
UE	
3	TAGE.
PROGRESS R	
×	m OF
	DESCRIPTION

TABLE 9 - VOLUME PRODUCTION SCHEDULE FOR FIRST WEEK'S PRODUCTION

1

:

PROCESS STEP	YIELD &	DEVICES/WK	RATE/HR	REQ'D/HR	PEOPLE REO'D.
Deliver Devices		2553			
Final Electrical Test	9.0	2808	48	74	1.5
Burn-In	100	2808			
Pre Burn-In Electrical	63	3847	48	101	2.1
Environmental Testing	100	3847			
' Attach Window	95	4039	52		1 3
Wire Bond to Chip	06	4443	20	111	5.6
Chip Mounting	80	5332	20.	133.	6.7
Wire Bond to Post	95	5599	48	140	2.9
Package Assembly	8 5	6439	200	160	1
					i i

TABLE 10 - VOLUME PRODUCTION RATES

### EPITAXIAL REQUIREMENTS

Diode chips required per week 5332

Maximum number of chips per wafer 2900

Number good electrical chips per wafer 1780

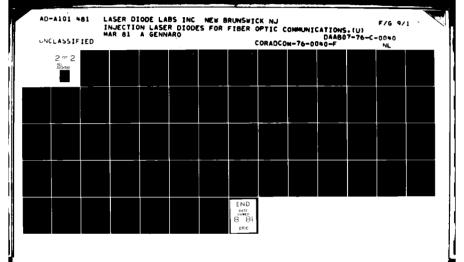
Number wafers required @ 50% yield 6

### EQUIPMENT REQUIREMENTS

2630 Burn-In positions @ \$ 180 per position
7 Assembly Stations @ \$ 2,000 per station
Epitaxial Furnace \$22,000
Power Measurement Test Set \$10,000

### PERSONNEL REQUIREMENT

Engineers 2
Technicians 2
Assembly 21



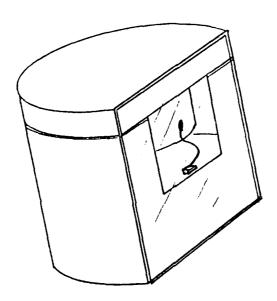
APPENDIX A
PRODUCT CAPABILITY DEMONSTRATION



# DEMONSTRATION SCHEDULE

# February 18, 1981

9:00 A.M.	-	Welcoming Session (Holiday Inn)
9:30 A.M.	-	Technical Presentation Program #8135
	-	Diode Specifications
	-	Diode Chip Concepts
	-	Packaging and Assembly Concepts
	-	Testing Methods
10:45 A.M.	-	Coffee
11:00 A.M.	-	Technical Presentation Program #0040
	-	Diode Specifications
	-	Diode Chip Concepts
	-	Packaging and Assembly Concepts
	-	Testing Methods
12:00 P.M.	-	Lunch
1:00 P.M.	-	Transport to LDL (Provided)
1:30 P.M.	-	Tour of LDL Facilities
	-	Demonstration of Diodes
2:30 P.M.		Transport to Holiday Inn (Provided)



CONTRACT DAABO7-76-C-0040
TRIPLE STRIPE LASER



U. S. ARMY CORADCOM SPECIFICATION DAABO7-76-C-0040 PRODUCT CAPABILITY DEMONSTRATION, FEBRUARY 18, 1981

## **OBJECTIVES**

# GENERAL MM&T PROGRAM OBJECTIVES

THE ESTABLISHMENT OF MANUFACTURING PROCESSES, TECHNIQUES OR EQUIPMENT TO ENSURE EFFICIENT PRODUCTION OF CURRENT OR FUTURE DEFENSE PROGRAMS.

# SPECIFIC OBJECTIVES

DEVELOP AND DEMONSTRATE A RELIABLE MONOLITHIC, LASER ARRAY CAPABLE OF 200 MW PULSED POWER OUTPUT AT 820 Mm AND 10% DUTY CYCLE CAPABLE OF BEING INTERFACED WITH A FIBER ARRAY.



# CONTRACT GOALS (LOGISTICS)

- \* ESTABLISH MANUFACTURING METHODS AND PROCESSES.
- \* ENGINEERING, CONFIRMATORY AND PILOT PRODUCTION PHASES.
- \* PILOT PRODUCTION CAPABILITY OF 200 DEVICES.



# CONTRACT GOALS (TECHNICAL)

- \* TRIPLE STRIPE MONOLITHIC LASER ARRAY.
- \* 200 MW PEAK OPTICAL POWER AT 10% DUTY CYCLE.
- \* WINDOW PACKAGE FOR FIBER INTERFACING.
- \* ENVIRONMENTAL CAPABILITY



# PROBLEMS ENCOUNTERED AND SOLVED

- \* DESIGN OF NARROW STRIPE PHOTO MASK.
- \* WINDOW FOF FIBER INTERFACING.
- \* EPOXIES FOR PACKAGE AND WINDOW ASSEMBLY.
- \* MECHANICAL STRENGTH OF PACKAGE.



# PRODUCTION CAPABILITY DEMONSTRATION PEGISTER - FEBRUARY 18, 1981

NAME:	COMPANY:
J, EIDE	ITT
B. HAWKINS	SPECTRONICS DIV., HONEYWELL
JACK HUNTER	CORADCOM U.S. ARMY
LOUIS CORYELL	CORADCOM U.S. ARMY
AL FEDDELER	U.S. ARMY CORADCOM
TED APPLE	CORADCOM
MARK D. SKELDON	NIGHT VISION LABS
LEN FELDBERG	BURNDY CORP.
DAM DAPKUS	ROCKWELL INTERNATIONAL
LOU TOMASETTA	ROCKWELL
GEORGE IRISH	GTE SYLVANIA
MARCUS GARVEY	GTE SYLVANIA
C.J. HWANG	GENERAL OPTRONICS
JOSEPH F. SVACEK	GENERAL OPTRONICS
KEN PEFFLEY	210
M. ETTENBERG	RCA
BOB GILL	LDL PRESIDENT
PETE SCHNEIDER	LDL EXECUTIVE VICE PRESIDENT
TOM STOCKTON	LDL VICE PRESIDENT E & D
STEVE KLUNK	LDL SALES ENGINEERING MANAGER
RICHARD KLEIN	LDL MARKETING MANAGER
AL GENNARO	LDL MANAGER SPECIAL PRODUCTS
ALEX CERUZZI	LDL MANAGER DEVELOPMENT ENGINEERING
ROLLIN BALL	LDL SUPERVISOR E & D
ANDY KAN	LDL MANAGER E/O ENGINEERING
STEVE LERNER	LDL MANAGER QUALITY ASSURANCE

# APPENDIX B

SCS-516 SPECIFICATIONS

### INJECTION LASER DIODE FOR USE IN FIBER OPTIC COMMUNICATIONS

### 1. SCOPE

1.1 Scope. This specification covers the detail requirements for Gallium Aluminum Arsenide (GaAlAs) injection laser diodes having a wavelength of 820 nanometers (nm). The injection laser (IL) devices shall incorporate the physical and electrical characteristics compatible with fiber optic cables and systems employing the use of fiber optics.

1.2 Recommended operating conditions:  $I_p = 3A$ 

 $T_a = 20^{\circ}C$ 

 $V_p = 2.0 \text{ V at } I_p = 3A$ 

### 2. APPLICABLE DOCUMENTS

2.1 The following documents, of the issue in effect on the date of invitation for bids or request for proposals, form a part of this specification to the extent specified herein:

#### SPECIFICATIONS

MILITARY

MI1-C-675

Coating of Glass Optical Elements.

MIL-S-19500

Semiconductor Devices, General Specification for.

#### STANDARDS

MILITARY

MIL-STD-202

Test Methods for Electronic and Electrical Component

Parts.

MIL-STD-750

Test Methods for Semiconductor Devices.

(Copies of documents required by contractors in connection with specific procurement functions chould be obtained from the procuring activity or as directed by the contracting officer. Both title and number or symbol should be stipulated when requesting copies.)

DAAB07 76 C-0040

SCS-516

2.2 Other publications. The following documents form a part of this specification to the extent specified herein. Unless otherwise indicated, the issue in effect on date of invitation for bids or request for proposal shall apply.

Laser Parameter Measurements Handbook, by H. G. Heard.

(Application for copies should be addressed to John Wiley & Sons, Inc., New York, N.Y.)

### 3. REQUIREMENTS

- 3.1 General description.— The II. devices are double heterojunction (FH) devices used at high data rates at a wavelength of 820 nm and shall be compatible with fiber optic cables. The operating temperature range shall be 20°C to 30°C.
- 3.2 Performance characteristics.— Performance characteristics shall be as specified in Tables III, IV and V.  $I_p$  is the value of the current to obtain peak pulse optical output power equal to 200 mV and shall have a minimum value of 3A. (See 4.6.5).  $I_p$  shall be determined for each device. This  $I_p$  value shall be the  $I_p$  value used for each device throughout the remainder of the document.
- 3.2.1 Process conditioning. All units shall be process conditioned. (See 4.5.1).
  - 3.2.2 Burn-In. All units shall be burned-in. (See 4.5.2).
- 3.3 Design, construction, and physical dimensions.— The design, construction and physical dimensions shall be as specified in Figures 1, 2, and 3 and herein.
- 3.3.1 <u>Metals.-</u> External metal surfaces shall be corrosion resistant or shall be plated or treated to resist corrosion.
- 3.4 <u>Window.</u>— The window shall contain no strain or cracks over the entire diameter and be free from optical distortion and lens effects over the central C.303 inch diameter. The window shall be anti-reflection coated on both surfaces for a wavelength of 7. = 820 nm. The coating shall conform to the abrasion resistance requirement of MIL-C-675.

- 3.5 Marking. Harking shall be in accordance with MIL-S-19500 except the following information shall be marked on each unit.
  - (a) Date code.
  - (b) Manufacturer's identification.
  - (c) Part number: SCS-516
- 3.6 Resistance to solvents. When the device is subjected to solvents, there shall be no evidence of: (a) mechanical or electrical damage, (b) deterioration of the materials or finishes, and (c) illegibility of case marking.
  - 3.7 Solderability .- Leads shall be solderable.
- 3.8 Thermal shock.— After being subjected to specified temperature cycling, there shall be no evidence of defects or damage to case, leads, or seals or loss of marking legibility.
- 3.9 Shock.— After being subjected to a shock of 500g for .5 msec, there shall be no evidence of defects or damage to leads or seals. Also, the device shall be electrically operable (see Subgroup 2 of Table III).
- 3.10 <u>Vibration fatigue</u>. After being subjected to a vibration with a constant peak acceleration of 20g minimum and a frequency of 60 ± 20 Hz for at least 32 ± 6 hours, there shall be no evidence of defects or damage to case, leads or seals. Also, the device shall be electrically operable (see Subgroup 2 of Table III).
- 3.11 <u>Vibration, variable frequency</u>.— After being subjected to a vibration with a constant peak acceleration of 20p minimum and a frequency range between 100 and 2000 Mz, there shall be no evidence of defects or damage to case, leads, or seals. Also, the device shall be electrically operable (see Subgroup 2 of Table III).
- 3.12 Constant acceleration. After being subjected to a constant acceleration of 1000g for 1 minute in each of its orientations, there shall be no evidence of defects or damage to case, leads, or seals. Also, the device shall be electrically operable (see Subgroup 2 of Table III).
- 3.13 Migh temperature life.— After being stored at 85°C for the specified time there shall be no evidence of defects or damage to case, leads or seals or loss of marking legibility. Also, the device shall be electrically operable (see Subgroup 2 of Table III).
- 3.14 Steady state operation. After being subjected to steady state operation ( $I_{\rm P} = 100~{\rm m}^2$ ) for the specified temperature and time, the device shall be electrically operable (see Subgroup 2 of Table III).
- 3.15 <u>Moisture resistance</u>.— After being subjected to the specified humidity and temperature cycling, there shall be no evidence of corrosion of external metal surfaces. Also, the device shall be electrically operable (see Subgroup 2 of Table III).

## 4. QUALITY ASSURANCE PHOVISIONS

- 4.1 Responsibility for inspection.— Unless otherwise specified in the contract, the contractor is responsible for the performance of all inspection requirements as specified herein. Except as otherwise specified in the contract, the contractor may use his own or any other facilities suitable for the performance of the inspection requirements specified herein, unless disapproved by the Government. The Government reserves the right to perform any of the inspections set forth in the specification where such inspections are deemed necessary to assure supplies and services conform to prescribed requirements.
- 4.2 <u>Classification of inspection.</u>— Inspection shall be classified as follows:
- (a) First article inspection (does not include preparation for delivery). (See 4.4).
  - (b) Quality conformance inspection. (See 4.5).
- 4.3 Test plan. The contractor prepared Government-approved test plan, as cited in the contract, shall contain:
  - (a) Time schedule and sequence of examinations and tests.
  - (b) A description of the method of test and procedures.
- (c) Identification and brief description of each inspection instrument and date of most recent calibration.
- 4.4 First article. Unless otherwise specified in the contract, the first article inspection shall be performed by the contractor.
- 4.4.1 First article units. The contractor shall furnish 50 samples for first article inspection.
- 4.4.2 First article inspection.— The first article inspection shall consist of Table II and all the tests included in the Government-approved test plan (See 4.3), to show compliance with the requirements of section 3. No failures shall be permitted.

- 4.4.2.1 Order of testing. Prior to first article inspection, all units shall have been process conditioned followed by burn-in: (See 4.5.1 and 4.5.2).
- 4.5 <u>Quality conformance inspection.</u>— Quality conformance inspection shall consist of the examinations and tests specified for Group A inspection (Table III), Group B inspection (Table IV), and Group C inspection (Table V). The following shall apply:
- (a) Prior to performing Group A inspection, all units shall be subjected to the tests specified in paragraphs 4.5.1 and 4.5.2.
- (b) If the manufacturer chooses the following option(s) for testing, the sample units that are to be used in Group C inspection shall be designated as such prior to conducting the referenced Group B tests. Moreover, the number of failed diodes to be counted for lot acceptance or rejection as a result of Group C test shall be equal to all failed diodes of the test in Group B inspection, which were predesignated for use in Group C inspection, plus any additional failures occurring during Group C testing.
- (1) For subgroup 3 life test in Group C inspection, the manufacturer has the option of using all or a portion of the sample already subjected to 340 hours of Group B life testing for an additional 660 hours of testing to meet the 1,000 hour requirement.
- (2) For the thermal shock (temperature cycling) test of Group C inspection, the manufacturer has the option of using all or a portion of the sample already subjected to 10 cycles of Group B thermal shock (temperature cycling) testing for an additional 15 cycles of testing to meet the 25-cycle requirement.
- 4.5.1 <u>Process conditioning.</u>— Process conditioning shall be performed on 100 percent of the units. The measurement and sequence shall be as specified in Table I.
- 4.5.2 Burn-In. Burn-In shall be performed on 100% of the units for 168 hours minimum under the following conditions:

 $I_p = (See 3.2)$   $T_a = 20^{\circ}C$  DF = 102

- 4.5.2.1 Pre-burn-in measurements.— Prior to burn-in, measurement of the parameters listed in subgroup 2 of Table III shall be performed on 100% of the units at  $T_a = 25\,^{\circ}\text{C}$ .
- 4.5.2.2 Post burn-in measurements.— Post burn-in measurements, listed in subgroup 2 of Table III, shall be performed within 8 hours of the removal of bias conditions at 25°C. The values observed for each device shall not exceed the following, relative to the pre-burn-in measurements:

$$\Delta \nearrow p = 1\%$$

$$\Delta P_{opt} = 1\%$$

Table I .- Frocess conditioning

Test	MIL-STD	Method No.	Details
High temperature life (non-operating)	<b>7</b> 50	1031	Storage temperature = 85°C Storage time = 48 hours minimum
Thermal shock	202	107	Test Condition A except t(high) = 85°C; t(low) = -10°C; time at temperature extremes = 15 minutes maximum
Constant acceleration	<b>75</b> 0	2006	1,000 g

Table II .- First article inspection

Reqt Para	Method .	No of samples 2/					
		3_		5	7	1.0	25
as specified	Table III y	To	be	peri	Cormed	on all	units
as specified	Table IV 1	x					
	•			X			
					x		
as specified	Table v 1/	χ					
				X			
3.13	Method 1031 of MIL-STD-750 T <sub>a</sub> = 85°C for 1000 hrs					X	
3.14	Method 1026 of MIL-STD-750 Ta = 25°C for 2000 hrs Ip = (See 3.2)						x
	as specified as specified as specified 3.13	as specified Table III \(\frac{1}{2}\) as specified Table IV \(\frac{1}{2}\)  as specified Table V \(\frac{1}{2}\)  3.13 Method 1031 of MIL_SID_750 Ta = 85°C for 1000 hrs  3.14 Method 1026 of MIL_SID_750 Ta = 25°C for 2000 hrs	as specified Table III 1/ To  as specified Table IV 1/  as specified Table V 1/  X  3.13 Method 1031 of MIL-STD-750  Ta = 85°C for 1000 hrs  3.14 Method 1026 of MIL-STD-750  Ta = 25°C for 2000 hrs 1p = (See 3.2)	as specified Table III 1/2 To be  as specified Table IV 1/2  as specified Table V 1/2  3.13 Method 1031 of HIL-SID-750 Ta = 85°C for 1000 hrs  3.14 Method 1026 of MIL-SID-750 Ta = 25°C for 2000 hrs Ip = (See 3.2)	as specified Table III \(\frac{1}{2}\) To be performance as specified Table IV \(\frac{1}{2}\)  as specified Table V \(\frac{1}{2}\)  x  3.13  Method 1031 of MIL-SID-750  Ta = 85°C for 1000 hrs  3.14  Method 1026 of MIL-SID-750  Ta = 25°C for 2000 hrs  Ip = (See 3.2)	as specified Table III \( \frac{1}{2} \)  as specified Table IV \( \frac{1}{2} \)  X  X  As specified Table V \( \frac{1}{2} \)  A X  3.13 Method 1031 of MIL-SID-750  Ta = 85°C for 1000 hrs  3.14 Method 1026 of MIL-STD-750  Ta = 25°C for 2000 hrs  Ip = (See 3.2)	as specified Table III \( \frac{1}{2} \)  as specified Table IV \( \frac{1}{2} \)  X  as specified Table V \( \frac{1}{2} \)  X  3.13 Method 1031 of MIL-STD-750 Ta = 85°C for 1000 hrs  3.14 Method 1026 of MIL-STD-750 Ta = 25°C for 2000 hrs  Ip = (See 3.2)  DF = 104

 $<sup>1/</sup>_{
m LTPD}$  values do not apply for first article inspection.

DAA807 76 C-0040

<sup>2/</sup>No. of samples specified for each column small be subjected to all the tests of that column.

<sup>3/</sup>After 2000 hours, the Popt shall equal 190 mW minimum.

Table III.- Group A inspection  $T_a = 25^{\circ}\text{C} \pm 2^{\circ}\text{C} \text{ unless otherwise specified}$ 

Test	Condition	Test Method	Min	Max	units	LTID
Subgroup 1						7
Visual and mechanical inspection		Method 2071 of MIL-STD-750	See	3.3		
Window		4.6.1				
Stripe width	I <sub>p</sub> = (See 3.2)	4.6.3				
(a) single (b) triple	t <sub>p</sub> = 10 ns DF = 10%		25 <b>7</b> 5		מחל עוול	
Subgroup 2						5
Peak wavelength	I <sub>p</sub> = (See 3.2)	4.6.4	800	830	nm	
Peak optical pulse power output	$I_p = (See 3.2)$	4.6.5	200		nM	
Subgroup 3				 } p',		5
Thermal impedance	1 <sub>p</sub> = (See 3.2)	4.6.6	10		°C	
	$t_p = 10 \text{ ns}$	.•				
Beam width	1 <sub>p</sub> = (See 3.2)	4.6.7				
(a) in junction plane	t <sub>p</sub> = 10 ns		15		angular degrees	
(b) perpendicular to junction				40	angular degress	

DAAB07 76 C-0040

Table IV. - Group is inspection

Test	Regt Para	MIL-STD-750 Method	Condition	LTPD
Subgroup 1 Physical dimensions	3.3	2071	See Figures 1, 2 & 3	15
Subgroup 2 Thermal shock (temperature cycling)	3.8	1051	Test Condition A except t(high) = 85°C; t(low) = -40°C; 10 cycles; time at temperature	15
Moisture resistance End point measurements Subgroup 2 of Table II		1021	extremes = 15 minutes maximum	
Subgroup ?				15
Shock Vibration fatime Vibration, variable frequency Constant acceleration End point measurements Subgroup 2 of Table II	:	2016 2046 2056 2006	Non-operating 500 g Non-operating Non-operating force applied = 1,000 g	
Subgroup 4				7
High temperature life (non-operating) (See 4.5(b))	3.13	1032	T <sub>2</sub> = 85°C	
End point measurements Subgroup 2 of Table 11			· ·	
Subgroup 5			•	5
Steady state operation life End point measurements Subgroup 2 of Table II	:	1027	$I_p = (See 3.2) at 50°C$ $DF = 10% (See 6.2)$ $t_p = 10 \text{ ns at } R_p = MHz$	

Table V.- Croup C inspection

Test	Reqt Para	MIL-STD-750 Method	Details	LTPD
Subgroup 1				15
Thermal shock (temperature cycling) (See 4.5(b))	3.8	1051	Test Condition A <sub>1</sub> except t(high) = 35°C; t(low) = 4.0°C; time at temperature extremes = 15 minutes, min; total test time = 72 hrs, max	
End point measurements: Suogroup 2 of Table III				
Subgroup 2				3 device
Resistance to solvents (See 4.6.2) End point measurements: Subgroup 2 of Table III	3.6	Method 215 of MIL-STD- 202		no fail
Subgroup 3				7
High temperature life (non-operating) (See 4.5(b))	3.13	1031	$T_a = 85$ °C for 1000 hrs	
End point measurements: Subgroup 2 of Table III				
Subgroup 4				5
Steady state operation life	3.14	1026	$I_p = (See 3.2)$ $T_a = 25°C \text{ for } 2600 \text{ hrs}$ $DF = 10\ell \text{ (See 6.2)}$	
End point measurements: Subgroup 2 of Table III	/	.•	,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,	

<sup>1/</sup>Limits of subgroup 2 Table III same except Popt = 190 mW min,

- 4.6 Test methods and conditions. Conditions and methods of examination and test shall be as specified in Tables 1, 11, 111, IV and V and as follows:
- h.6.1 <u>Window.-</u> Visual inspection shall be made to insure there are no cracks or optical distortions in the window.
- 4.6.2 Resistance to solvents. Resistance to solvents shall be performed in accordance with Method 215 of MIL-STD-202.
- 4.6.3 Stripe width. The stripe width size can be determined by using a microscope objective and a normal lens (for projection) combination with a magnification of at least 200%. The image shall be scanned in the junction plane with a calibrated ITT Phototube #F4000 (see 6.3), masked with an 0.5 mm slit. Slit shall be perpendicular to the direction scanned. The relative intensity shall be measured until it falls to 90% of its peak value. These boundaries will define the stripe width. (See Figure 4).
- 4.6.4 Feak wavelength ( >p).- Peak wavelength shall be measured using a grating spectrometer with a resolution of at least one angstrom.
- h.6.5 Peak optical pulse power (Popt).— Popt is measured using a calibrated ITT Phototube #F4000 terminated into 50 ohrs positioned at a distance of 1.5 cm with a rectangular aperture of width .39 cm and length 1.03 cm. (See Figure 6). (See 6.3).
- 4.6.6 Thermal impedance.— With unit mounted on a heat sink capable of being heated above room temperature, it is driven at 0.1% duty cycle to minimize self-heating effects. Measurements of peak output wavelength ( $\nearrow$ p) versus temperature (T) from 20°C to L0°C are recorded. In order to take into account its own heating effect, unit is then operated at 20°C and at 10% duty cycle. The peak cutput wavelength is then recorded under these conditions. The voltage drop ( $V_D$ ) across the output of the unit is then measured. (See 6.2).
- 4.6.7 Bean width. A calibrated ITT Phototube #F4000 (see 6.3), shall be mounted on a turntuble and masked with a small aperture so that is angular resolution is at least one degree. The distance between the unit and the detector shall be at least 20 cm. The relative intensity shall be measured until its value falls down to 50% of its peak value. This area will define the beam width. The beam width in angular degrees is measured in both the junction plane and in the plane perpendicular to the junction plane. (See Figure 5).

## 5. PREPARATION FOR DELIVERY

5.1 Preservation, packaging and packing. - Units shall be prepared for delivery as specified in the contract.

## 6. NOTES

6.1 Abbreviations, symbols, and definitions. The abbreviations, symbols, and definitions are as follows:

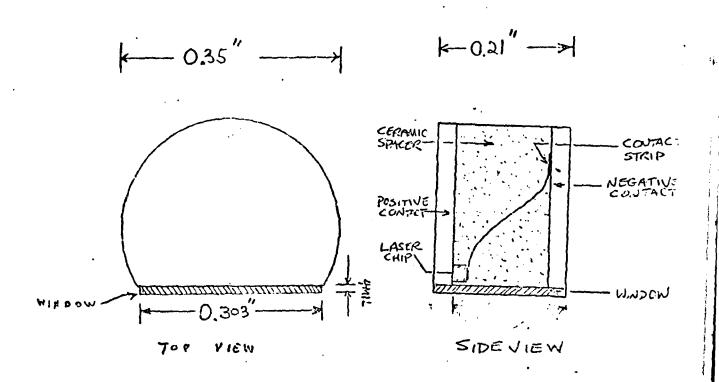
DF	duty factor
$\mathtt{I}_{\mathbf{p}}$	input pulse current
Popt	peak pulse optical power output
Ta	ambient temperature
$t_p$	pulse width at 3 db point
$R_{\mathbf{p}}$	pulse repetition rate
$v_{F}$	forward voltage
<b>7</b> p	peak wavelength

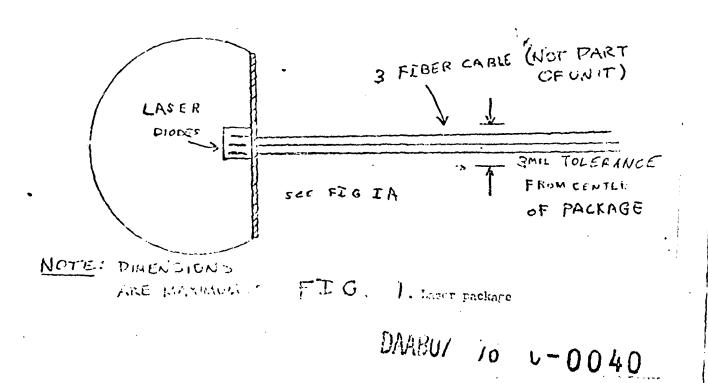
6.2 Calculation of thermal impedance ( $Z_t$ ).- Thermal impedance can be calculated by taking the slope ( $\propto$ ) of the curve  $\rightarrow$  vs temperature measured in 4.6.6 and the following:

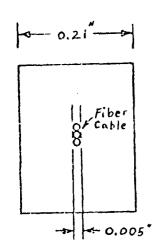
$$Z_t = \frac{\Delta T}{\Delta P}$$
 where  $\Delta P = I_p \times VD \times DF$  and  $DF = T_p \times t_p$   
 $\Delta T = \frac{\Delta Y}{\Delta P}$  - where  $\Delta T$ , and  $\Delta Y$  are taken from graph

6.3 <u>Method for calibration of ITT phototube #F1000.</u>— This information can be found on pages 190 to 190 in "laser Parameter Measurements Handbook." Manufacturer's calibration is acceptable if traceable to an NPS standard.

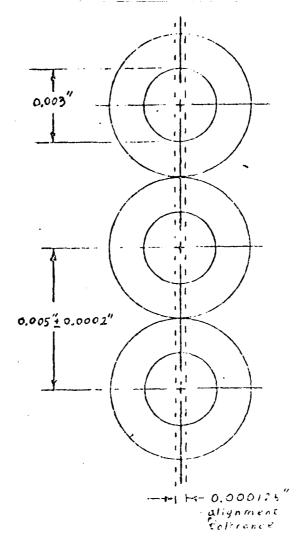
DAAB07 76 C-0040







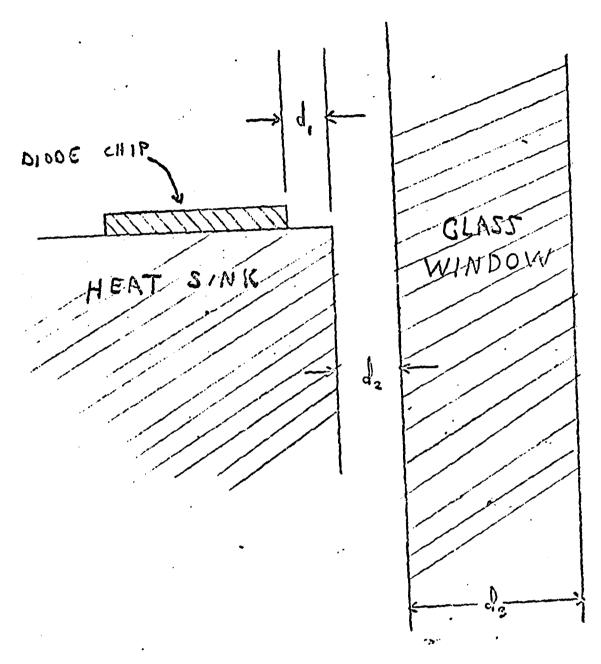
Fiber cable aligned with injection laser



Optical Fiber Cable

Figure IA. Filer calls (NIT PART OF UNIT)

DAMBO7 76 C-0040

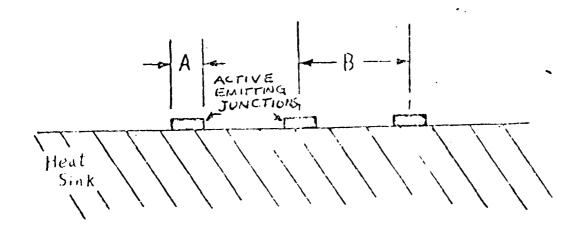


• (MAN) 
$$\partial_{1} = 1 \text{ MIL } (0.0254 \text{ MM})$$

$$\partial_{2} = 1.5 \text{ MIL } (0.0381 \text{ MM}) \pm .5 \text{ MIL}$$
(MIN)  $\partial_{3} = 5 \text{ MIL } (0.101614M)$ 

$$(MAN) = 5 \text{ MIL } (0.101614M)$$
Figure 2. Mounting disconting
$$0 \text{ MAEOV } 76 \text{ C-004}$$

# TRIPLE STRIPE GEOMETRY

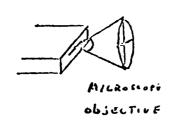


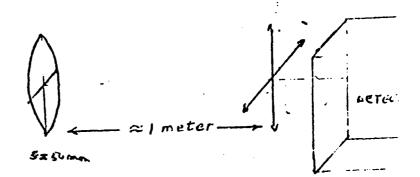
DIMENSION	INCHES	MM
A(MAX)	0.001	25
В	0,005, ±0,000?	125

FIG. 3 FRONT VIEW OF DIODE ASSEMBLY

DAA307 76 | C-0040.

1 1





FRONT VIEW

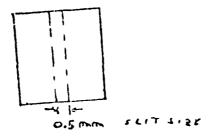


Figure 4. Stripe width

DAAB07 76 C-0040

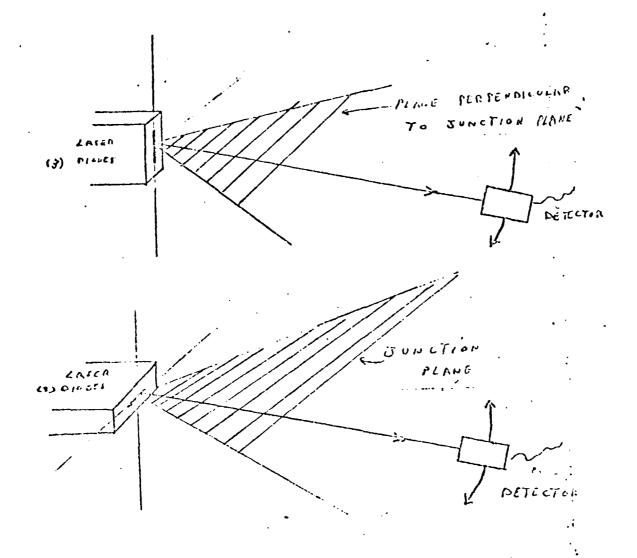
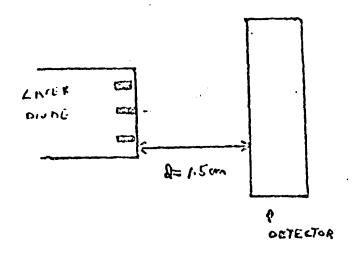
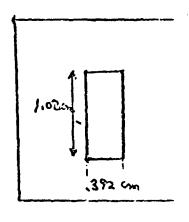


Figure 5. Beam width

DAAB07 76 C-0040





OF BETECTS

FIG. 6 LASER POWER MEASUREMENTS

DAA807 76 C-0040

## INJECTION LASER DIODE FOR USE IN FIELE OPTIC COMMUNICATIONS

# Page 1

1.2 line 2, delete "20°C" and substitute "25°C"

#### Page 2

- 3.2 line 3, delete "minimum" and substitute "maximum"
- 3.4 delete and substitute:
- "3.4 Window. The window shall contain no strain or cracks over that portion which is in the optical path (area of input radiation incident on the injection laser chip). This portion of the window shall also be free from optical distortion and lens effects. The window shall be anti-reflection costed on both surfaces for a wavelength of 7 = 820 nm. The coating shall conform to the abrasion resistance requirement of MIL-C-675."

### Page 3

- 3.7 delete in its entirety.
- 3.14 line 2, delete " $(I_F = 1.00 \text{ mA})$ "

## Page 5

4.5.2 line 4, delete "20°C" and substitute "25°C"

## Page 8

Table III, Subgroup 3, Thermal impedance, under units column, delete ""C" and substitute ""C/d"

## Page 9

Table IV, Subgroup 5, under Condition column, delete "50°C" and substitute "25°C" for  $\rm I_p$ 

DAAB07 73 C-0040

## Page 10

Table V, Subgroup 2, under Details column for Resistance to solvents, add, mexcept solvents used shall be:

- (a) Methyl alcohol, per 0-Ni-232, Grade A.
- (b) Ethyl alcohol, per 0-E-00760, Type 1, Grade A.
- (c) Isopropyl alcohol, per TT-I-735, Grade A.
- (d) Three (3) parts by volume of isopropyl alcohol, as specified in (c) above and one (1) part by volume of distilled water."

## Page 11

- 4.6.1 Add, "This test shall be performed prior to attaching the window to the case."
- 1.6.2 Add, "except solvents used shall be:
  - (a) Methyl alcohol, per 0-M-232, Grade A.
  - (b) Ethyl alcohol, per O-E-00760, Type 1, Grade A.
  - (c) Isopropyl alcohol, per TT-I-735, Grade A.
- (d) Three (3) parts by volume of isopropyl alcohol, as specified in (c) above and one (1) part by volume of distilled water."
- 4.6.5 line 3, delete ".39 cm" and substitute ".394 cm" line 3, delete "1.03 cm" and substitute "1.09 cm"
- 4.6.6 lines 4 and 5, delete "20°C" and substitute "25°C"

## Page 19

Fig 6 Front view of detector, delete "1.03 cm" and substitute "1.09 cm"
Delete ".392 cm" and substitute ".394 cm"

DAAB07 73 C-0040

ELECTRONICS COMMAND
TECHNICAL REQUIREMENTS

SCS-516 AMENDMENT -2 20 April 1976

# INJECTION LASER DIOLE FOR USE IN FIBER OFFIC COMMUNICATIONS

# Page 8

Subgroup : - Suring width (a) single - change "25 mm minimum" to "25 mm maximum."

Stripe width (b) triple - change "75 rm minimum" to "75 mm maximum."

Subgroup 3 - Thermal impedance - change "10° c/w minimum" to "10° c/w maximum."

Beam width (9) in junction plane - change "15 angular degrees minimum" to "15 angular degrees maximum."

ELECTRONICS CONTAIN TECHNICAL REQUIREMENTS SCS-516
AMENDMENT-2
20 April 1976

# INJECTION LASER DIODE FOR USE IN FIBER OPTIC COMMUNICATIONS

# Page 8

To Table III - Subgroup 3, add:

		Test			
Test	Condition	Method	Min	Max	Units /
Average Optical Power Output Per Stripe	I <sub>p</sub> = (see 3.2) t <sub>p</sub> = 10 ns	4.6.8 & . 6.4	6.3	7.0	mW ·

# Page 11 4.6.8 Power Uniformity from Stripe to Stripe

Laser stripe must be magnified to 200 x using a lens that has a f number of 1.2. The projected images of each of the three junction faces must be tested for average power using a silicon photodiode.

# Page 12

6.4 Definition of average optical power Average optical power = Peak optical power / 10

Average optical power/stripe = 1/3 average optical power.

HATGARD FORM JU, JULY 1966 -ENFRAL SERVICES ADMINISTRATION -PER PROC. NO. 141, CER. 1-14, 101		/MODIFICATION OF CONTRACT $\begin{bmatrix} 1 & 2 & 2 \\ 1 & 2 & 2 \end{bmatrix}$				
MOU ICATION NO POOCOL	See.	BLOCK I	UISITION/PURCHASE REQUE	EST NO	A PROJECT NO 11/ ap	
ISSUED BY		below ·	V/A AINISTERED BY (If other if	han block \$1	CODE	1-2210IV
CHMUNICATIONS SYSTEM	S PROCUREMENT	ВКИПСН	The second secon	<b>U</b> ( ( ( ) )	(01)	531021
IR OF PROCUREMENT, C			DCASMA - Spri	ngfield		
J 07703; Buyer/Symbo	ol: Captain	L'Heureux	240 Route 22	•		
RSEL-PC-C-CS-2(LHE)	Phone: 201-53	2-4775	Springfield,	NJ 0708:	1	
CONTRACTOR CODE	4D33L	FACILITY C		7.		
NAME AND ADDRESS			<u> </u>	AMENDME		
				SOLICITAT	ION NO.	
LASER DIODE I	LABORATORIES,	INC.	•	DATED	(See b	lack 0.1
Street, city, 205 Forrest	Street			Į.	, , , , , , , , , , , , , , , , , , , ,	•
and ZIP Metuchen, NJ	08817			MODIFICAT	TACKET NO. DAABO	)7-76-C-004C
(ode)				1-		
<u>L</u>				DATED_	76 JUN 30 (S., )	lack 11)
				<u></u>		
THIS BLOCK APPLIES ONLY TO AMENDA						
The above numbered solicitation is an						
Offerers must acknowledge receipt of this		•			=	
(a) By signing and returningcopies which includes a reference to the solicita						
DATE SPECIFIED MAY RESULT IN REJECT	TION OF YOUR OFFER.	If, by virtue of this ame	ndment you desire to change	on offer already	submitted, such change ma	
or letter, provided such telegrom or letter		olicitation and this amen	dment, and is received prior	to the opening h	our and date specified.	
). ACCOUNTING AND APPROPRIATION D	ATA (If required)				CONTRACT	ODIC CON
N/A					CONTRACT	UK 2 CUPY
. THIS BLOCK APPLIES ONLY TO MODIFI	CATIONS OF CONTRACTS	o Orders				
(a) This Change Order is issued pu						
The Changes set forth in block 1						
(b) The above numbered contract/o		3 C L .				n black 12.
(c) XX This Supplemental Agreement i			al Agreement	or cire ba	tretes.	
It modifies the above numbered		ck 12.				·····
2. DESCRIPTION OF WHEN DARENE / MODIF			I			
This Supplemental Agr	reement is enf	tered into b	y the parties	to amend	the basic Sn	ecification
(SCS-516) as well as	to redefine f	the Pilot Pr	oduction Run (	(CLIN OOC	OLAC).	001110001011
				`	,-	
		]	I			
Section E - Supplies/	'Services is a	amended as f	ollows:			
Delete:	Block 19 in i	its entirety				
		-				
Add: Pil	ot Run shall	consist of	fifty (50) eac	h Single	Stripe, fift	v (50) each
Dou	ble Stripe, a	and two-hund	red (200) each	ı Triple	Stripe units	in accordan
wit	h SCS-516 dat	ted 29 Decem	ber 75 and Ame	endment N	o. 4 to SCS-5	16 dated
4 N	lovember 77.			,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,	0. + 00 000-)	10 dated
	,,-					
Section F - Descripti	on/Specificat	ion is amen	ded as follows	3:		
_	, -			. •		
Subsectio	n F.49, Paras	raph 2c - D	elete "The car	pacity of	each operation	on" and
8 W D D 0 1 0 W 0	e uncreiore	THE WILLIAM	capacity of e	ach oper	ation.	
cept as provided herein, all terms and con  3.	dillons of the socument ret	rerenced in Block 8, 65 i	eretorore changed, remain un	ichanged and in tu	1 COPY	
CONTRACTOR/OFFEROR IS NOT	REQUIRED TO CONTR	ACTORZÓFEERÓX IS RI	QUIRED TO SIGN THIS DO	CUMENT AND RE	ETURN KONAKAY TO	ISSUING OFFICE
·- ·- ·			שווות שווונט			
THANK OF COMPRACION/ON \$40X 1.	THE THE CONTRACTOR	O.ULIONILIA),	i i u i i i i i i i i i i i i i i i i i	K-1/X-17 - 5/1	i narratata	
T	of person authorized to sig	in)	- BY	(Signatur	re of Contracting Officer)	<del></del>
S. NAME AND TITLE OF SIGNER (Type		16. DATE SIGNED	18. NAME OF CONTRAC			19. DATE SIGNED
J. FORME ACM THE OF STORER (1)PE	p,	The signed	STEPHEN L. T		- year or princip	JAIL STORED
			Major, Signa			}
		I	, , , , , , , , , , , , , , , , , , , ,	£		1

Modification P00001 to: Contract No. DAAB07-76-C-0040

Section F - Description/Specification is amended as follows (Cont'd):

Subsection F.49, Paragraph 2d

Delete "The yield of each operation at the specified rate"

and substitute therefore "The estimated yield of each operation at the specified rate."

Subsection F.2

"Add" - Amendment No. 4 4 Nov 77 to SCS-516.

III

PCO responsibility for subject contract is hereby transferred from Mr. Gordon E. McMain to Major Stephen L. Thacher, DRSEL-PC-C-CS-2(THA) 201-532-3506.

IV

Inclusion of the above changes shall be at no additional cost to the Government. All other terms and conditions of this contract remain unchanged.

ELECTRONICS COMMAND
TECHNICAL REQUIREMENTS

SCS-516 AMENDMENT-4 4 NOVEMBER 1977 SUPERSEDING AMENDMENT-3 15 JULY 1976

## INJECTION LASER DIODE FOR USE IN FIBER OPTIC COMMUNICATIONS

This amendment forms a part of Electronics Command Technical Requirements SCS-516
15 August 1975

## Page 1

- 1.2 line 2, delete "20°C" and substitute "25°C"
- 2.1 add the following under SPECIFICATIONS

"FEDERAL

O-E-00760 Ethyl Alcohol (Ethanol); Denatured Alcohol; Proprietary
Solvents and Special Industrial Solvents.
O-M-232 Methanol (Methyl Alcohol).
TT-I-735 Isopropyl Alcohol."

## Page 2

- 3.2 line 3, delete "minimum" and substitute "maximum"
- 3.4 delete and substitute:
- "3.4 Window.- The window shall contain no strain or cracks over that portion which is in the optical path (area of input radiation incident on the injection laser chip). This portion of the window shall also be free from optical distortion and lens effects. The window shall be anti-reflection coated on both surfaces for a wavelength of  $rac{1}{2}$  = 820 nm. The coating shall conform to the abrasion resistance requirement of MIL-C-675."

#### Page 3

- 3.7 delete in its entirety
- 3.14 line 2, delete " $(I_F = 100 \text{ mA})$ "

SCS-516
AMENDMENT-4

## Page 5

- \* Add the following paragraph:
  - "4.4.2.2 Procedure in case of test equipment failure or operator error. If a device is believed to have failed as a result of faulty test equipment or operator error, the failure shall be entered in the test record which shall be submitted to the Government along with a complete explanation verifying why the failure is believed to be invalid. The Government will then decide whether or not the failure is due to a valid part defect. If the Government rules that the failure is invalid, a replacement device from the same inspection lot may be added to the sample. The replacement device shall be subjected to all those tests to which the discarded device was subjected prior to its failure and to any remaining specified tests to which the discarded device was not subjected prior to its failure."
- \* Add the following subparagraph to paragraph 4.5:
  - "(c) Procedure in case of test equipment failure or operator error. If a device is believed to have failed as a result of faulty test equipment or operator error, the failure shall be entered in the test record which shall be submitted to the procuring activity along with a complete explanation verifying why the failure is believed to be invalid. The procuring activity will then decide whether or not the failure is due to a valid part defect. If the procuring activity rules that the failure is invalid, a replacement device from the same inspection lot may be added to the sample. The replacement device shall be subjected to all those tests to which the discarded device was subjected prior to its failure and to any remaining specified tests to which the discarded device was not subjected prior to its failure."
  - 4.5.2 line 4, delete "20°C" and substitute "25°C"

#### Page 6

\* 4.5.2.2 line 6, delete " $\triangle P_{opt} = 1$ "and substitute " $\triangle P_{opt} = 5$ "

Table III, delete and substitute the following:

"Table III.- Group A inspection  $T_a = 25^{\circ}C + 20^{\circ}C$  unless otherwise specified

Test	Condition	Test Method	Min	Max	Units	LTPD
Subgroup 1						7
Visual and mechanical inspection		Method 2071 of MIL-STD-750	See 3	.3		
Window		4.6.1				
Stripe width	I <sub>p</sub> = (See 3.2)	4.6.3			;	
<ul><li>(a) single</li><li>(b) double</li><li>(c) triple</li></ul>	t <sub>p</sub> = 10 ns DF = 10%			25 50 75	יירל א שול שול	
Subgroup 2						5
Peak wavelength	I <sub>p</sub> ≈ (See 3.2)	4.6.4	800	830	nm	
Peak optical pulse power output	$I_{p} = (See 3.2)$	4.6.5				
<ul><li>(a) single</li><li>(b) double</li><li>(c) triple</li></ul>			65 130 200		mW mW mW	
Subgroup 3		· · · · · · · · · · · · · · · · · · ·				5
Thermal impedance	$I_p = (See 3.2)$	4.6.6				
(a) single	$t_p = 10 \text{ ns}$			30	oc/M	
<pre>(b) double (c) triple</pre>				15 10	oc/M	
Beam width	I <sub>p</sub> = (See 3.2)	4.6.7				
(a) in junction plane	$t_p = 10 \text{ ns}$			15	angular degrees	
(b) perpendicular to junction				40	angular degrees	
Power uniformity from stripe to stripe	I <sub>p</sub> = (See 3.2) t <sub>p</sub> = 10 ns	4.6.8		10%	1/	

<sup>1/</sup> Any device in which the relative power output of the weakest stripe is less than 90% of the relative power output of the most powerful stripe shall be rejected.

SCS-516
AMENDMENT-4

#### Page 9

Table IV, Subgroup 5, under Condition column, delete "50°C" and substitute "25°C" for Ip

## Page 10

- Table V, Subgroup 2, under Details column for Resistance to solvents, add, "except solvents used shall be:
  - (a) Methyl alcohol, per 0-M-232, Grade A.
  - (b) Ethyl alcohol, per O-E-00760, Type 1, Grade A.
  - (c) Isopropyl alcohol, per TT-I-735, Grade A.
- (d) Three (3) parts by volume of isopropyl alcohol, as specified in (c) above and one (1) part by volume of distilled water."

### Page 11

- 4.6.1 Add, "This test shall be performed prior to attaching the window to the case."
- 4.6.2 Add, "except solvents used shall be:
  - (a) Methyl alcohol, per 0-M-232, Grade A.
    - (b) Ethyl alcohol, per 0-E-00760, Type 1, Grade A.
    - (c) Isopropyl alcohol, per TT-I-735, Grade A.
- (d) Three (3) parts by volume of isopropyl alcohol, as specified in (c) above and one (1) part by volume of distilled water."
- 4.6.3 delete and substitute:
  - "4.6.3 Stripe width. The stripe width size can be determined by using a closed circuit TV based system. A 40% microscope objective shall be used to project an image with magnification of at least 200% of the laser on a sheet of metric graph paper. This image, after being reduced in intensity by insertion of suitable attenuation in the laser beam path is in turn picked up via the TV camera. The combined images of the laser and the grid shall be displayed on the screen of the TV monitor. Since the stripe spacing is determined with a high degree of accuracy by the photolithographic mask, the magnification of the projection system may readily be determined. The stripe width may, therefore, be measured directly without requiring XY calibration of the TV system. An oscilloscope shall be used to monitor the video waveform and insure that the TV camera is not being saturated."

- \* 4.6.5 delete and substitute:
  - "4.6.5 Peak optical pulse power (Popt) Popt is measured using a calibrated avalanche photodiode diode system terminated into 50 ohms positioned at a distance of 1.5 cm with a rectangular aperture of width 0.39 cm and length 1.03 cm. (See Figure 6 and paragraph 6.3)."
  - 4.6.6 lines 4 and 5, delete "20°C" and substitute "25°C"
- \* 4.6.7 delete and substitute:
  - "4.6.7 Beam width. With the laser mounted in a rotatable pulser, the detector head of a calibrated E.G. & G. model 460 is placed at least 65 cm away to obtain an angular resolution of at least one degree. The relative intensity shall be measured until its value falls to 50% of its peak value. This area will define the beam width. The beam width in angular degrees is measured in both planes parallel and perpendicular to the junction. (See Figure 5)."

## Page 12

- \* Add the following new paragraph:
  - "4.6.8 Power uniformity from stripe to stripe. Using a CCTV system as outlined in 4.6.3, the video waveform from the TV camera shall be monitored on an oscilloscope. The peaks of the video waveform correspond to the relative powers from the individual stripes.
- \* 6.3 delete and substitute:
  - "6.3 Method for calibration of the avalanche photodiode (APD) system. Using ten representative triple stripe lasers pulsed at low duty cycle, measurements shall be made with both the APD and an NBS traceable ITT F4000 tube. In both cases the separation between source and detector shall be as small as possible to insure collection of all the energy and good correspondence. Correlation of these data will give a calibration factor for the APD system."

## Page 13

- \* Add new paragraph:
  - "6.3.1 Method for relative calibration of the TV system amplitude response. Focus the TV camera on a standard grey scale with known reflectance values. The resulting video waveform voltages monitored on an oscilloscope will correspond proportionally to these valves and will permit drawing a relative calibration curve for the amplitude response of the TV system."

SCS-516
AMENDMENT-4

Add the following paragraph:

"6.4 Calculation of average optical power.

Average optical power =  $P_{opt}/10$ 

Average optical power/stripe = 1/3 average optical power."

Page 13

FIG 1. Delete FIG 1. and substitute new FIG. 1.

Page 14

FIGURE 1A. Delete "0.21" dimension and substitute ".300 + .005"

Page 17

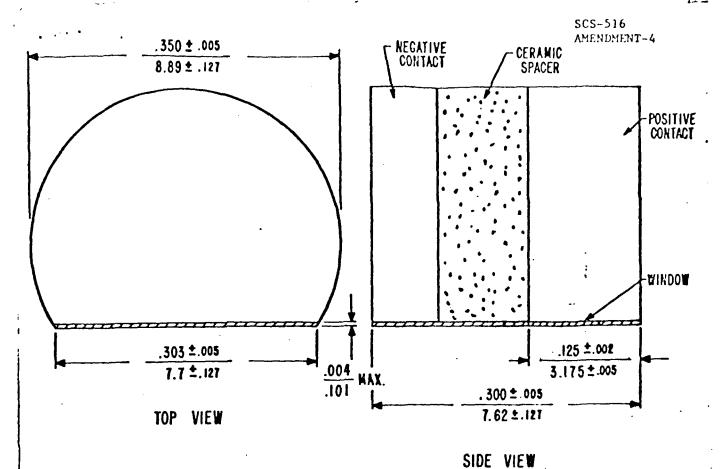
Figure 4, delete in its entirety.

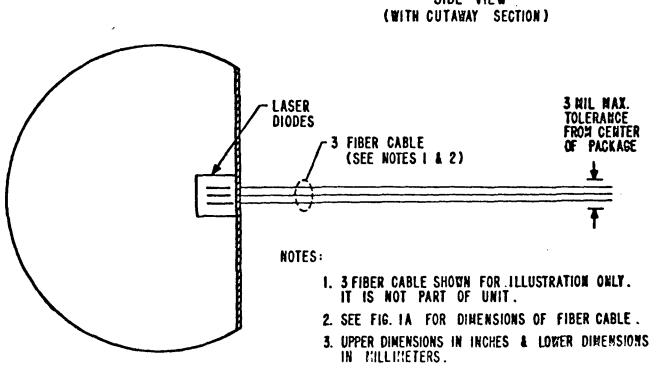
Page 19

FIG 6 Front view of detector, delete "1.03 cm" and substitute "1.09 cm"

Delete ".392 cm" and substitute ".394 cm"

NOTE: The margins of this amendment are marked with an asterisk to indicate where changes (additions, modifications, corrections, deletions) from the previous amendment were made. This was done as a convenience only and the (vernment assumes no liability whatsoever for any inaccuracies in these notations. Bidders and contractors are cautioned to evaluate the requirements of this document based on the entire content irrespective of the marginal notations and relationship to the last previous amendment.





STANDARD FORM 30, JULY 1966 GENERAL SERVICES ADMINISTRATION FEC. PROC. NEG. (41 CPR) 1-16-101			/MO	DIFICATION O	F CONTRACT	PAGE   OF
MODIFICATION NO. FU0002	3.6 S.6	e Block 19	REQUISITION/PURCHASE N/A	REQUEST NO.	4. PROJECT NO. (If ap	plicable)
A. BANED BY  COMMUNICATIONS SYSTEM  PROCUREMENT BRANCH, I  FOCUREMENT, SERCOM,  COURTE FUNCT CYMBOL:  DROEL-PO-C-CS-2-LHE	CODE WI	LSP7T OF IH, NJ	DCASMA-Sprin 240 Route 22 Springfield,	gfield	CODE	
CODE NAME AND ADDRESS  LASEF DIODE (Street, clty, county, sleet, c	Street 7 08817	IES, INC.	TY CODE	[=		2-76-C-0040
The above numbered solicitation is on Officers must acknowledge receipt of this (a) by signing and returning copin which technice a reference to the solicite DATE SPECIFIED MAY RESULT IN REFECT OF Inter, provided such tologreen or letter 10. ACCOUNTING AND APPROPRIATION ET.//A.  11. THIS BLOCK APPLIES ONLY TO MODIF	emendment prior to s of this amendment, iften and emendment IDN OF YOUR OFF makes reference to DATA (If required)	the hour and date aps (b) By acknowledging of numbers. FAILURE ( ER. If, by virtue of th the solicitation and thin	scified in the solicitation, or o receipt of this amendment of DF YOUR ACKOWLEDGMEI is amendment you desire to	is amended, by one of the on each copy of the offer NT TO BE RECEIVED AT T change an offer already	following methods: r submitted; or (c) By separate tSSUING OFFICE PRIO submitted, such change may	R TO THE HOUR AND
(a) This Change Order is issued por The Changes set forth in block in the changes set forth in block in the changes set forth in block in the change of the	2 are made to the ab order is modified to n s entered into pursue contract as set forth I I ON	what the administrative of State of Sta	ubsection L.2	(ASPR 7-103.	2 Changes).	
Section H, Deliveries amended as follows:	or Perfor	rmance, and	Modification		8 September s After Effec	
0004 (0005) Pilot 0006 - Production ( 0007 (E001) Produc	Report on ( Report ral Report t Line Rate Capability ction Capal stration P	Step II Report Demonstrat	y Samples		310 930 300 720 330 1050 330 1050 370 990  310 930 330 1050	
13. CONTRACTOR/OFFEROR IS NOT TO SIGN THIS DOCUMENT			IS REQUIRED TO SIGN TO		I COPY	ISSUING OFFICE
14. NAME OF CONTRACTOR	LASER DIODI INC.	E LABORATOR	IES, 17. UNI	TED STATES OF		
(Signature 15. NAME AND TITLE OF SIGNER (Type of	of person authorized ( or <i>print)</i>	16. DATE SIQU	h	(Signature Ontractin <b>g Officer (</b> BEEKMAN	of Contracting Officer) Type or print)	19. DATE SIGNED

Modification No. P00002 to: Contract No. DAAB07-76-C-0040

II

The consideration for this extension in Delivery Schedule is the additional tasks required to fabricate one and two stripe devices as outlined in Modification POOOOl to this Contract (currently awaiting execution by Contractor).

III

Inclusion of the above changes shall be at no additional cost to the Government. All other terms and conditions of this Contract remain in effect.

GENERA SERVICES ADMINISTRATION PED PROG. REG. (41 CFR) 1-16-101		MODIFICATION (	OF CONTRACT 1 3					
	Fee Block 19	JISITION/PURCHASE REQUEST NO	4. PROJECT NO. (If applicable)					
	PECTORATE NJ 07703 E	DCASMA, Springfield 240 Route 22 Bringfield, NJ 07081	CODE 53101A					
7 CONTRACTOR NAME AND ADDRESS  LASER DIODE LABORATORIES, INC.  (Street, ctr., 205 Forrest Street and / IP Metuchen, NU 08817  7 This block applies only to amendment for solk(Ifations)  The agains numbered solk(ration is amended as set forth in black 12. The hour and date specified for receipt of Offers a extended.  Offerors must actional returningcopies of this amendment; (b) by acknowledging receipt of this amendment or set was a solicitation and amendment numbers. FAILURE OF YOUR ACKNOWLEDGMENT TO BE RECEIVED AT THE ISSUING OFFICE PRIOR TO THE HOUR AND DATE SPECIFIED MAY RESULT IN REJECTION OF YOUR OFFER. If, by virtue of this amendment you desire to change on offer already submitted. Such change may be made by relegram or latter provided inch fellogram or latter provided inch fellogram or latter makes reference to the solicitation and amendment on the solicitation and sended on the solicitation and amendment numbers. AND DATE SPECIFIED MAY RESULT IN REJECTION OF YOUR OFFER. If, by virtue of this amendment you desire to change on offer already submitted, such change may be made by relegram or latter provided inch fellogram or latter makes reference to the solicitation and amendment, and is received prior to the opening hour and date specified.  10 ACCOUNTING AND APPROMENTION DATA (If regumed)								
(a) This SLOCK APPLES ONLY TO MODIFICATIONS OF CONTRACTS/ORDERS  (b) The Obanges set form in block 12 are made to the above numbered contract/order.  (b) The above numbered contract/order is modified to reflect the administrative changes (such as changes in paying affice, appropriation date, stc.) set form in block 12.  (c) This Supplemental Agreement is entered into pursuant to authority of the modifies the above numbered contract as set forth in block 12.  12 DESCRIPTION OF MODIFICATION  Contract DAABO7-76-C-0040 is changed as follows:  I  Section F, Description/Specifications, is amended as follows:								
Section F.46, Subparagraph 4:  Charge Commander, US Army Electronics Command, ATTN: DRSEL-CT-LD to Commander, US Army Electronics Research and Development Command, ATTN: DELNV-L-C and Commander, US Army Electronics Command, ATTN: DRSEL-PP-I-PI-1 to Commander, US Army Electronics Research and Development Command, ATTN: DELSD-D-PC.								
13.	1 COMPACTO ACTUACION IS NOT MODULED CON							
14 NAME OF CONTRACTOR/OFFEROR		17. UNITED STATES OF AMERICA						
IS NAME AND TITLE OF SIGNER (Type or print)	16. DATE SIGNED	18. NAME OF CONTRACTING OFFICER STEPHEN L. THACHER Major, Signal Corps						
			1 "A} 1 c					

- 130 -

...

Section H, Items 0001AB, B002, D001:

Change Commander, US Army Electronics Command, ATTN: DRCEL-RD-ET-2, Fort Monmouth, NJ 07703 to Commander, US Army Electronics Research and Development Command, ATTN: DELNV-L-C, Fort Monmouth, NJ 07703.

Section H. Items 2001, 2002, 2004, 2005, E001

Change Commander, US Army Electronics Commander, ATTN: DRSEL-PP-I-1, Fort Monmouth, NJ 07703 to Commander, US Army Electronics Research and Development Command, ATTN: DELSD-D-PC, Fort Monmouth, NJ 07703.

Section I, Inspection and Acceptance, is amended as follows:

Section 1.14 - Change Commander, US Army Electronics Command, ATTN:
DROEL-CT-LD, Fort Monmouth, NJ 07703 to Commander,
US Army Electronics Research and Development Command,
ATTN: DELNV-L-C, Fort Monmouth, NJ 07703.

Change Commander, US Army Electronics Command, ATTM: DESEL-RD-ET-2, Fort Monmouth, NJ 07703 to Commander, US Army Electronics Research and Development Command, ATTN: DELNV-L-C, Fort Monmouth, NJ 07703.

Change Commander, US Army Electronics Command, ATTN: DRSEL-PP-I-PI-1, Fort Monmouth, NJ 07703 to Commander, US Army Electronics Research and Development Command, ATTN: DELSD-D-PC, Fort Monmouth, NJ 07703.

## Section K, Contract Administration Data, is amended as follows:

Delete: Subsection  $K_{\bullet}2(a)$  in its entirety and substitute therefore:

The Purchasing Office Representative is:

NAME: CPT Roy W. L'Heureux

ORGANIZATIONAL CODE: DRSEL-PC-C-CS-2(LHE)

TELEPHONE AREA CODE AND NO.: (201)-532-1412

Section M is amended as follows:

DD 1423 Form Exhibit B, Item BOO2 and Exhibit D, DOO1:

Change Code W15P7N to W15P8S.

Modification P00003 to: Contract No. DAAB07-76-C-0040

II

PCO responsibility for this contract has changed as follows:

FROM

<u>TO:</u>

Mr. Gordon McMain DRSEL-PC-C-CS-1 STEPHEN L. THACHER
Major, Signal Corps
DRSEL-PC-C-CS-2(THA)
Phone: (201)-532-3506

STANDARD FORM 30. JULY 1966  SET-PAL SERVICES ADMINISTRATION FED 1900 FEQ. 41 JFR) 1 16. JD  AMENOMENT OF SOCIETATION/MODIFICATION OF CONTRACT  1 9		
DAABO7-76-C-0040, P00004 See Blk 19 M/A		
USACORADCOM, Procurement Directorate Proc Div D, Ft. Monmouth, N.J. 07703 Mr. John C. Hunter/DRDCO-PC-D(HUN) (201) 532-1716  CODE W15BAY  DCASMA, Springfield 240 Route 22 Springfield, New Jersey 07081	S3101A	
TAME AND ADDRESS CODE 4031 FACILITY CODE		
FERTURE LE SOLICITATION NO		
Laser Diode Laboratories, Inc. 1130 Somerset Street	5-C-0040	
	Mark Ite	
THE BLUCK APPLIES ONLY TO AMENOMENTS OF SOLICITATIONS		
The accept numbered solicitation is amended as set forth in block 12. The hour and date specified for receipt of Offers is extended is not extended.		
Offerors must acknowledge receipt of this amendment onor to me hour and date specified in the solicitation, or as amended, by one of the inviewing methods.  as dysigning and returning		
The spiriclation and amendment numbers. FAILURE OF YOUR ACKNOWLEDGMENT TO BE RECEIVED AT THE ISSUING OFFICE PRIOR TO THE HOUR AND DATE SPECIFIED MAY RIVOUR OFFICE. PRIOR TO THE HOUR AND DATE SPECIFIED MAY RIVOUR OFFICE. They write of this amendment you desire to change an offer amendment, such is necessed prior to the opening nour and date specified.	ESULT IN RELECTION OF	
O ACCOUNTING AND APPROPRIATION DATA -// Tremed)		
1. This alock applies only to modifications of contracts. Orders		
ar This Change Critics is issued pursuant to		
The Changes set forth in block 12 are mage to the above numbered contract/order.		
b) The above numbered contractional is invested to relief the administrative changes is such as changes in paying office, appropriation data, etc.) set forth in breck 12.  (i) This Suppremental Agreement is entered into oursuant to authority of Changes, Provision, Subsection L2 of the co	ntract	
t modifies the appeal numbered contract as set forth in block 12.	mer de c.	
2 DESCRIPTION OF AMENOMENT MODIFICATION		
PROJECT: MANUFACTURING METHODS AND TECHNOLOGY PROGRAM OF INJECTION LASER DIODETIN FIBER OPTIC COMMUNICATIONS.	FOR USE	
•		
*		
PART II, THE SCHEDULE, SECTION E is amended as follows:		
Add SLIN 0001AD to SUPPLIES/SERVICES		
"0001AD Three (3) each LASER STACKS		
LDL Part No. IRE 167 No Cost"		
	•	
	•	
	·	
Extends as provinced never and remarktions of the decument remnenced in block if as neverofore changed remain unchanged and in full force and effect		
Extent as provided never all terms and conditions of the document referenced in block 8, as neverties changed, remain unchanged and in full force and effect.  1. IONIZACTIS OFFEROR IS NOT REQUIRED  1. CODV TO SIGN THIS DOCUMENT AND RETURN 1 CODV TO SIGN THIS DOCUMENT AND RETURN 1.	ISSUING OFFICE	
CODY SANTRACTOR SEFFECE S NOT REQUIRED TO SOME THIS DOCUMENT AND RETURN 1 CODY	issuing office	
ONTRACTOR OFFEROR S NOT REQUIRED  ONTRACTOR/CRORENT S REQUIRED TO S ON THIS DOCUMENT AND RETURN I CODY ONTRACTOR/CRORENT IS REQUIRED TO S ON THIS DOCUMENT AND RETURN I CODY ONTRACTOR/CRORENT IS REQUIRED TO S ON THIS DOCUMENT AND RETURN I CODY ON THE OFFEROR ON THIS DOCUMENT AND RETURN I CODY ON THE OFFEROR S AMERICA  S GNATURE OF DEPORT AND RETURN IS SIGNIFICATION.	ung.	
DISCHIPACTOR SEFEROR IS NOT REQUIRED TO SOME PRODUCE OF THIS DOCUMENT AND RETURN TO CODY TO SIGN THIS SOCUMENT AND RETURN TO SOME TO THE STATES OF AMERICA TO SOME THE SOME	ISSUING OFFICE  19 JAYE SIGNED  17 NOV 129	

uşÇ.

Contract No. DAABO7-76-C-0040 Modification No. P00004 Laser Diode Laboratories, Inc. Page No. 2 of 9

Ιī

PART II, THE SCHEDULE, SECTION F, Description/Specifications, is amended as follows:

1. Subsection F.48, Subparagraph 6 - Delete this paragraph in its entirety and substitute the following:

### "6. Additional Confirmatory Sample Test Requirements:

Twenty-five (25) Confirmatory Samples will be subjected to a 2000 Hour Life Test. Upon completion the samples will be retested in accordance with Table II. The Life Test and Table II (Retest) data will be incorporated into the Final Report. The Life Test samples shall be shipped to the Government upon completion of tests."

2. Add the following subparagraph to SECTION F:

### "F.50 FINAL REPORT - SUPPLEMENTAL INSTRUCTIONS

The Final Report shall be prepared in accordance with the requirements as specified by CDRL CQO3. In addition, the report shall contain an Executive Summary, Pilot Line Rate Data, and Life Test Data."

III

PART II, THE SCHEDULE, SECTION H, Deliveries or Performance:

DELETE the contents of this Section in its entirety and SUBSTITUTE the following:

CLIN/SLIN	ITEM	DELIVERY DATE
0001AA	Engineering Samples Total 26 each (Lot 1 & 2)	Received & Accepted Nov 1977
0001AB	Confirmatory Samples 25 each (Lot 1)	Received & Accepted 3 July 1979
	25 each (Lot 2) (Life Test Units)	Not Later Than 27 Feb 1981

Contract No. DAABO7-76-C-0040 Modification No. P00004 Laser Diode Laboratories, Inc. Page No. 3 of 9

## REVISED DELIVERY OR PERFORMANCE SCHEDULE (Continued)

CLIN/SLIN	ITEM	DELIVERY DATE
3001AC	Pilot Run Samples 50 each Single Stripe Units	Received & Accepted
	50 each Double Stripe Units	15 Aug 1980 Received & Accepted
	200 each Triple Stripe Units	24 Sep 1980 5 Dec 1980
0001AD	LASER STACKs - 3 each	Not Later Than 27 Feb 1981
0002/A001	PERT	Received & Accepted
0003/8001	Engineering Sample Test Report (For Lots 1 & 2)	Received & Accepted
0003/3002	Confirmatory Sample Test Report (For Lots 1 & 2 except Life Test)	Received & Accepted
0004/C001	Monthly Technical Reports	
	Reports for July 1976 thru Sep 1980	Received & Reviewed
	Oct 1980 Report	Not Later than
	Nov 1980 Report	10 Nov 1980 Not Later than
	Dec 1980 Report	10 Dec 1980 Not Later than 10 Jan 1981
0004/0002	Quarterly Reports Reports for Sep 1976 thru Aug 1980	Received & Reviewed
	Oct 1980 Report	Not Later Than 10 Nov 80
0004/0003	Final Report	
	Oraft Final	14 Nov 1980 27 Feb 1981

The second secon

12

Contract No. DAAB07-76-C-0040 Modification No. P00004 Laser Diode Laboratories, Inc. Page No. 4 of 9

### REVISED DELIVERY OR PERFORMANCE SCHEDULE (Continued)

CLIN/SLIN	ITEM	DELIVERY DATE
0004/C004	<pre>General Report - DELETED   (Incorporated as "Executive Summary"   in Final Report)</pre>	
0004/C005	Pilot Line Rate Report - DELETED (Incorporated in the Final Report)	
0005/D001	Test Plan (Confirmatory Sample)	Received & Accepted
0006	Production Capability Demonstration	11 Feb 1981
	Draft Invitation Letter Industry Invitation Letters	12 Dec 1980
	(Mailed By)	16 Jan 1981
0007/E001	Production Capability Demonstration Plan	
	Draft	12 Dec 1980
	Final ·	16 Jan 1981
0008AA	Life Tests	Completion Not Later Than 20 Feb 1981

I۷

PART II, THE SCHEDULE, SECTION I - Inspection and Acceptance -

DELETE the contents of this Section in its entirety and SUBSTITUTE the following:

### "I.14 INSPECTION AND ACCEPTANCE

CLIN/SLIN	ITEM	FINAL INSPECTION/ACCEPTANCE PERFORMED BY: *
0001AA	Engineering Samples	Received & Accepted
0001AB	Confirmatory Samples Lot 1 Lot 2 (After Life Test)	Received & Accepted DELNV-L

Contract No. DAABO7-76-C-0040 Modification No. P00004 Laser Diode Laboratories, Inc. Page No. 5 of 9

### INSPECTION AND ACCEPTANCE (Continued)

CLIN/SLIN	ITEM	FINAL INSPECTION/ACCEPTANCE PERFORMED BY: *
0001AC	Pilot Run Samples Single Stripe Units Double Stripe Units Triple Stripe Units	Received & Accepted Received & Accepted DELNV-L
0001AD	Laser Stack Units	DELNV-L
0002/A001	PERT	Received & Accepted
0003/B001	Engineering Sample Test Report	Received & Accepted
0003/B002	Confirmatory Sample Test Report	Received & Accepted
0004/C001	Monthly Technical Reports Oct/Nov/Dec 1980 Reports	DELNV-L
0004/C002	Quarterly Reports Oct 1980 Report	DELNV-L
0004/C003	Final Report Draft Final	DELNV-L DELNV-L
0005/D001	Test Plan (Confirmatory Sample)	Received & Accepted
0006	Production Capability Demonstration Draft Invitation Letter	DELNV-L DRDCO-PC-D
0007/E001	Production Capability Demonstration Plan Draft Final	DELNV-L DELNV-L
0008AA	Life Tests	DELIIV-L

<sup>\*</sup>Responsibility codes used are not to be construed as full address identifiers. Full addressees and "SHIP TO" data cited below.

Contract No. DAAB07-76-C-0040 Modification No. P00004 Laser Diode Laboratories, Inc. Page No. 6 of 9

INSPECTION AND ACCEPTANCE (Continued)

Verification of the capability of the contractor to fabricate the devices at the specified rate for the pilot run will be performed at the factory of the contractor during performance of the pilot run by:

\*DELNV-L and/or DRDCO-COM-RM-1

Inspection and Acceptance of the Devices under SLIN 0001AC Triple Stripe Units (pilot run) will be performed at the factory of the contractor by:

\*DCASMA

Final Inspection and Acceptance of the Production Capability Demonstration, CLIN 0006, will be made at time of demonstration by:

\*DELNV-L and/or DRDCO-COM-RM-1 and/or DRDCO-PC-D

Location of demonstration will be as mutually agreed by the contractor and the Contracting Officer prior to Invitation Letter issuance.

Inspection and Acceptance of SLIN 0008AA will be performed at the factory of the contractor by:

\*DCASMA and/or DRDCO-COM-RM-1

Address listings with "SHIP TO" or "MARKED FOR" data shall be used when shipping hardware or software (data) items.

For Code DELNV-L:

SHIP TO:

Property Officer, USA MERADCOM Bldg 335 Fort Belvoir, VA 22060

MARKED FOR:

Commander
USA ERADCOM
ATTN: DELNV-L (Mr. Skeldon)
Fort Belvoir, VA 22060

Contract No. DAABO7-76-C-0040 Modification No. P00004 Laser Diode Laboratories, Inc. Page No. 7 of 9

INSPECTION AND ACCEPTANCE (Continued)

For Code DRDCO-COM-RM-1:

Commander USA CORADCOM CENCOMS

ATTN: DRDCO-COM-RM-1 (Mr. L. Coryell) Fort Monmouth, New Jersey 07703

For Code DRDCO-PC-D:

Commander USA CORADCOM

Procurement Directorate

ATTN: DRDCO-PC-D (Mr. J. C. Hunter) Fort Monmouth, New Jersey 07703

For Code DCASMA:

DCASMA, Springfield

240 Route 22

Springfield, New Jersey 07681

ATTN: DCRNGSCC-S4 (Mr. J. Martorano) Contract DAABO7-76-C-0040"

PART II, THE SCHEDULE, SECTION K, CONTRACT ADMINISTRATION DATA, is amended as follows:

- 1. Subsection K.1, PLACE OF PERFORMANCE, subparagraph 1, DELETE in its entirety and SUBSTITUTE the following:
- "1. The work called for herein will be performed by the contractor at the following locations:

ITEM NO.

LOCATION OF

A11

Final Manufacture Packaging and Packing Shipping Point

New Brunswick, New Jersey 08901 New Brunswick, New Jersey 08901 New Brunswick, New Jersey 08901

Contract No. DAABO7-76-C-0040 Modification No. P00004 Laser Diode Laboratories, Inc. Page No. 8 of 9

CONTRACT ADMINISTRATION DATA (Continued)

ITEM NO.

LOCATION OF

Producing Facilities

Locations

Laser Diode Laboratories, Inc., Owner

1130 Somerset Street

New Brunswick, New Jersey 08901

105 Forrest Street

Metuchen, New Jersey 08817

Contractor's office which will receive payment, supervise and administer the contract:

1130 Somerset Street New Brunswick, New Jersey 08901"

2. Subparagraph K.2, subparagraph a., DELETE in its entirety and SUBSTITUTE the following:

"Name:

John C. Hunter

Organization:

USA CORADCOM

Procurement Directorate

Attn: DRDCO-PC-D(HUN)
Fort Monmouth, New Jersey 07703

Telephone No.:

(201) 532-1716/3306

Autovon No.:

992-1716/3306"

۷I

PART IV, SECTION M is amended as follows:

DD Form 1423 Data Requirements, pages 51 through 56 revised - copies attached.

VII

The consideration for this extension in delivery is the additional tasks required to fabricate CLIN 0001AD items.

Contract No. DAAB07-76-C-3040 Modification No. P00004 Laser Diode Laboratories, Inc. Page No. 9 of 9

IIIV

PCO responsibility for this contract has changed as follows:

FROM:

Stephen L. Thacher Major, Signal Corps DRSEL-PC-C-CS-2 (THA) Phone (201) 532-3506

TO:

Joseph E. Feeney Contracting Officer United States of America Phone (201) 532-1716

IX

Inclusion of the above changes shall be at no additional cost to the Government. All other terms and conditions of this contract remain unchanged and in effect.

Initiating Activity: CORADCOM/CENCOMS Prev Allot No.: 2162035 6627510 P5297 2510 S28043

JCH/gms

APPENDIX C

DISTRIBUTION LIST

RCA Laboratories
David Sarnoff Research Center
Princeton, NJ 08540
ATTN: Dr. M. Ettenberg

Rockwell International 1049 Camino Dos Rios PO Box 1085 Thousand Oaks, CA 91360 ATTN: Dr. P.D. Dapkus

TRU Technology Research Center 2525 East El Segundo Blvd El Segundo, CA 90245

ATTN: H.D. Law

Variar, Central Research Laboratories 611 Hansen Wow Palo Alto, CA 94303 ATTN: Dr. R. L. Bell

Lasertron, Inc 8 Alfred Circle Bedford, MM 61730 ATTN: Dr. J.'. Halen Reliability Analysis Center ATTN: RBRAC (Mr. I. Krulac) Criffiss AFB, NY 13441

Commander, Rome Air Development Center ATTN: RADC/DCCI (Mr. P.Sierak) Criffiss AFB, NY 13441

Commander
US Army Satellite Communications Agency
Fort Monmouth, NJ 07703
ATTN: DRCPM-SC-3

Commander
US Army Avionics Research and
Development Activity
ATTN: DAVAA-D
Fort Monmouth, NJ 07703

ITT Electro-Optical Products Div 7635 Plantation Road Roanoke, VA 24019 ATTN: Mr. R. McDevitt

Hughes Aircraft Comp Tucson Systems Engrg. Dept. PO Box 80. Tucson, AZ 65734 ATIM: Mr. D. Fox Tri-Tac Office ATTN: TT-DA (Mr. C. Arnold) Fort Monmouth, NJ 07703

Advisory Group on Electron Devices ATTN: Secy, Working Group D(Lasers) 201 Varick Street New York, NY 10014

Raytheon Company Communications Systems Directorate Equipment Division 528 Boston Post Road Sudbury, MA 01776 ATTN: Mr. T. Kelly

General Optronics Corp 3005 Hadley Road South Plainfield, NJ 07080 ATTN: P.W. Hankin

Motorola, Inc.
High Frequency and Optical Products Div
5005 East McDowell Road
Phoenix, AZ 85008
ATTN: J.C. Herman

The Plessey Company, LTD
Allen Clark Research Center
Caswell, Towcester
Northants, England NNIE BEQ
ATTN: R. Davis

Commander Naval Ocean Systems Center Code 4400 San Dieto, CA 92152 Attn: Nr. R. Lebduska

Commander Naval Ocean Systems Conter Attn: Library San Diego, CA 92152

Parris Government Comm Systems Div. P.O. Box 37 Melbound, FL 32901 Abtn: Mr. R. Tainter

1TT Defense Communications Paraklet 492 River Rud Nutley, NJ 07110 Attn: Dr. P. Sueensny

OTE Products Corp Communications System Divisio: 189 P Street Needham Heights, Mr. (2194

Commander Naval Avionics Facility Code D831 Indianapolis, IN 46218 Attn: Mr. R. Katz Mitre Corp. p.o. Box 208 Bedford, MA 01730 Attn: Mr. R. Hazel

7

National Schedu of Standurds Electromagnetic Tech Div Boulder, CC 80303 Attn: Dr. G. Day

Defense Logistics Agency Arth: DESC-EMT (Mr. A. Hudsen) Dayton, OH 45444

Commander
Air Force Avionics Laborator,
Attn: AFAL/AAD-2 (Mm. K. Trumble)
Wright-PattersonAFB, CH 45853

CDR, US Army Signals Warfure Lab Attn: DELSW-OG Arlington Hall Station Arlington, VA 22212

CDR, US Army Signals Warfam Jub Attn: DELSW-AV Arlington Hall Station Arlington, VA 20012

Commander
US Army Logistics Conter
Attn: ATCL-MC
Fort Lee, VA 20001

Commander
US Army Training & Doctrine Command
Attn: ATCD-TEC
Fort Monroe, VA 23651

Commander
US Army Training & Doorrine Command
Attn: ATCD-TM
Fort Monroe, VA 23651

MASA Scientific & Tech Info Facility Baltimore/Nashington Intl Airport P.O. Box E757 Baltimore, MD 21249

CDR, US Army Research Office Attn: DPVRO-IP P.O. Box 12211 Research Triangle Park, NC 27709

Director N.S. Army Material Systems Analysis Actr. Attn: DRXSY-MP Joerdeen Proving Ground, MD 21005

Admisory Group in Electron Devices 201 Varick Street, 9th Floor New York, NY 10014 Commander ERADCOM Fort Manuality, NJ 07703 Attn: DEBMT9D

Commander
ERADCO:
Fort Mommouth, NJ 07703
Attn: DUSD-I-S

Commander CECOM Fort Monmouth, NJ 07703 Attn: DRSEL-COM-D

Commander CECOM Port Monrouth, NJ 07703 Attn: DRSEL-SEI

Commander
CECOM
Fort Monmouth, NJ 07703
ATTN: DRSEL-COM-RM-1 (Mr. L. Coryell)
(8 copies)

### DISTACBULICA LIST

Defense Technical Information Center Attn: DTIC-TCA Cameron Station (Building 5) Alexandria, VA 22314 (12 Oppies)

Director National Security Agency Attn: TDL Fort George G. Meade, MD 20755

Code R123, Tech Library
DCA Defense Comm Engrg Ctr
1860 Wiehle Avenue
Reston, VA 22090

Defense Communications Agency Technical Library Center Obde 205 (P.A. Tolovi) Washington, DC 20305

Office of Naval Research .Code 427 Arlington, Va 22217

GIDER Engineering & Support Dept. TE Section P.O. Box 398
Norco, CA 91760

CDR, MICOM
Redstone Scientific Info Center
Attn: Chief, Document Section
Redstone Arsenal, AL 35809

Commander
HQ Foru Huachuca
Attn: Technical Reference Div
Fort Huachuca, AD 85613

Commander
US Army Electronic Proving Ground
Attn: STEEP-MT
Fort Huachuca, AN 85613

Commander
USASA Test & Evaluation Content
Attn: IAO-COR-T
Port Huachucz, AZ 85613

Director Naval Research Laboratory Attn: Code 2627 Washington, DC 20375

Command, Control & Communications Div.
Development Center
Marine Corps Development & Educ Comd
Quantico, VA 22134

Naval Telecommunications Command Technical Library, Code 911 4401 Massachusetts Avenue, NA Washington, DC 20390

Rome Air Development Center Attn: Documents Library (TILT). Griffiss AFB, N.Y. 13441

HQDA (DAMM-ARP/DR. F.D. Verderame) Washington, DC 20310

Director
US Army Human Engineering Labe
Abordeen Proving Ground, 12 71005

CDR, AVRANCOM Attn: DRSAV-2 P.O. Box 209 St. Louis, MO 63166

Director
Joint Comm Office (TRI-TAC)
Attn: FT-AD (Tech Docu Cun)
Fort Monmouth, NJ 07703

Dir.,US Army Air Mobility R&D Lab Attn: T. Cossett, Bldg. 200-5 NASA Ames Research Center Noffett Field, CA 94035

HODA (DAM)-TNE) Washington, DC 10310

Deputy for Science & Technology office, Tablet Dec Army (DkD) Washington DC 20310

Commander, DARCOM Atun: DRODE 5001 Eisenhower Avenue Alexandric, 17, 22323

## END

# DATE FILMED 8

DTIC